leti 2008

INSTITUT CARNOT CEA LETI

MINATEC®

CMOS Nanoelectronics scaling and Technology Diversifications

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Tokyo Institute of Technology
Yokohama, Japan, June 17, 2011

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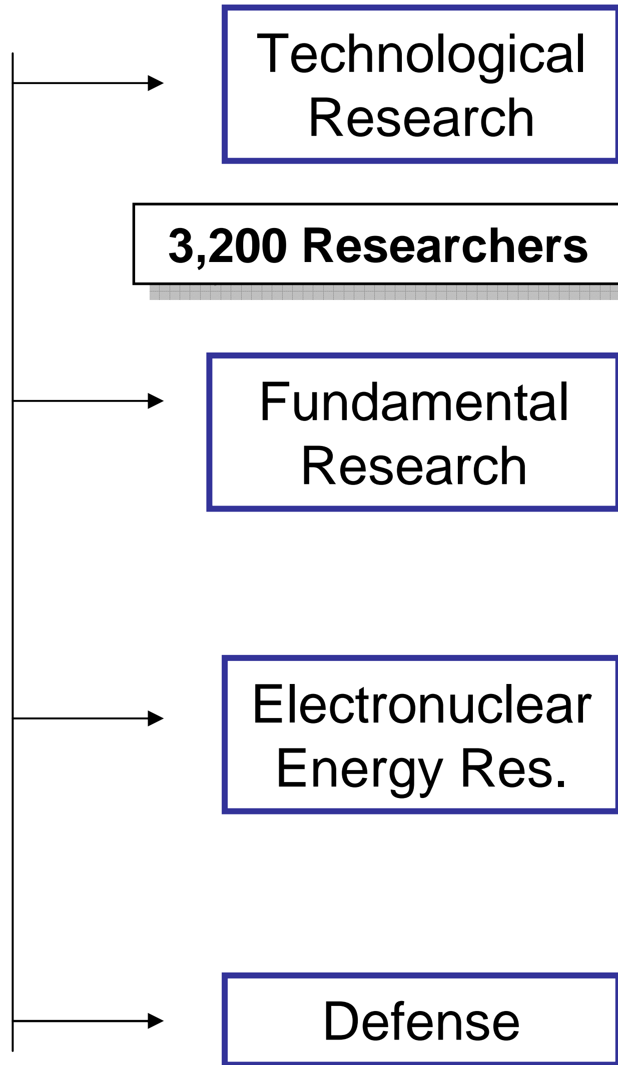
cea

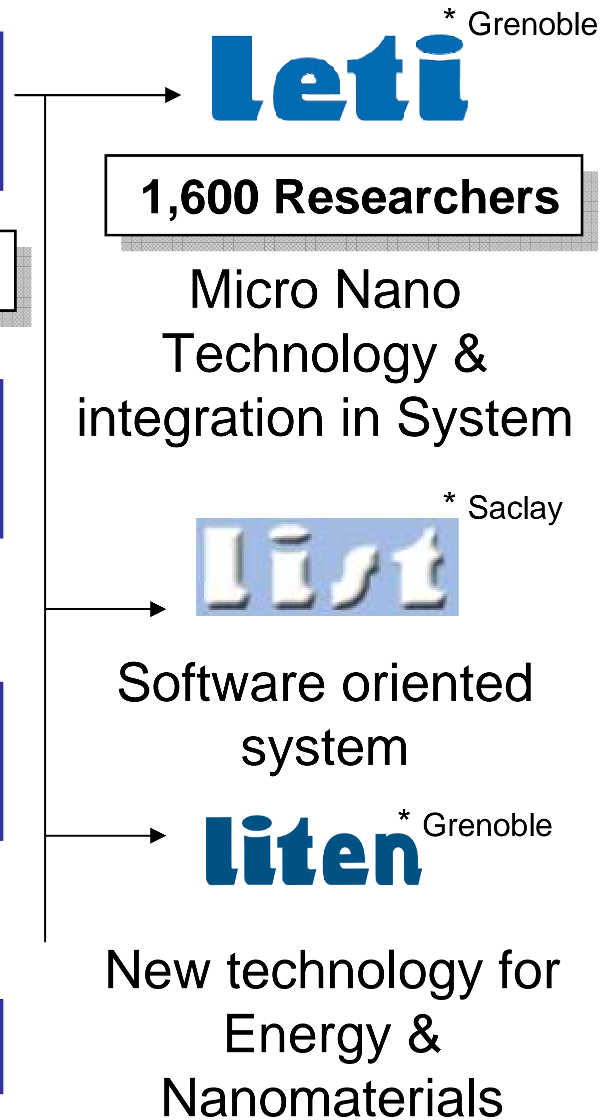
CEA – LETI organization

French Nuclear Agency

15,000 Employees

3 billion € Budget





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LETI: Mission and Focus

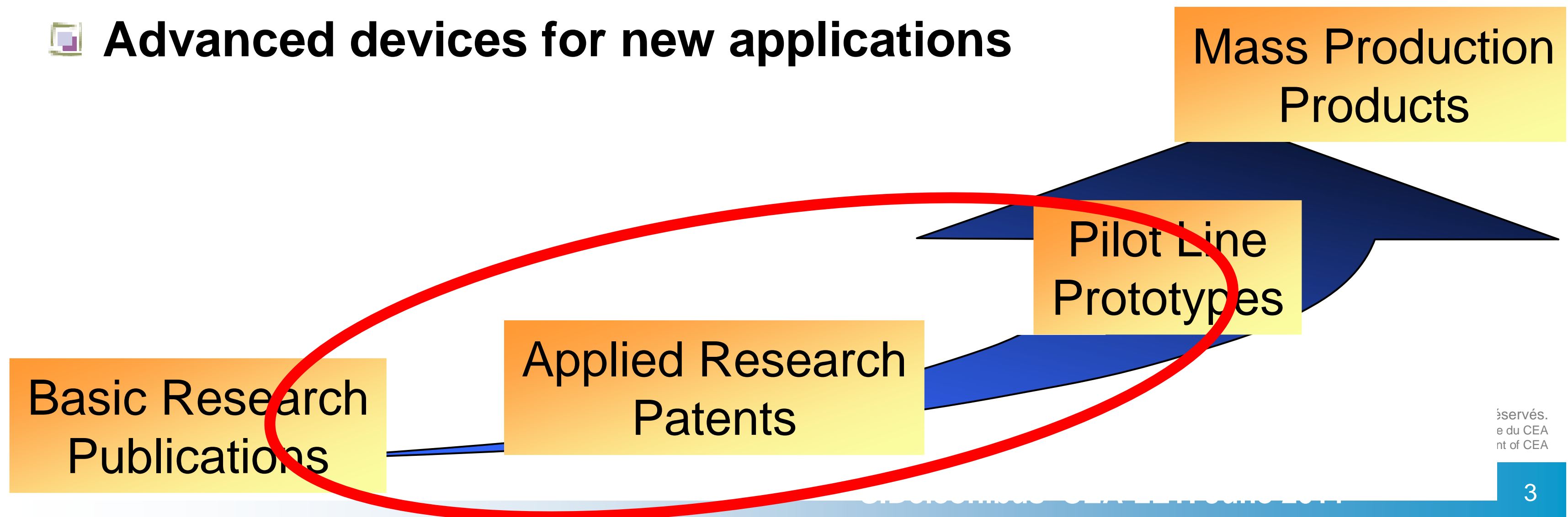
INSTITUT CARNOT CEA LETI
MINATEC®

- A single mission :

  Create innovation

  & transfer it to industry

- A clear focus :
  - **µ-nanotechnologies, with critical mass in Si**
  - **Advanced devices for new applications**



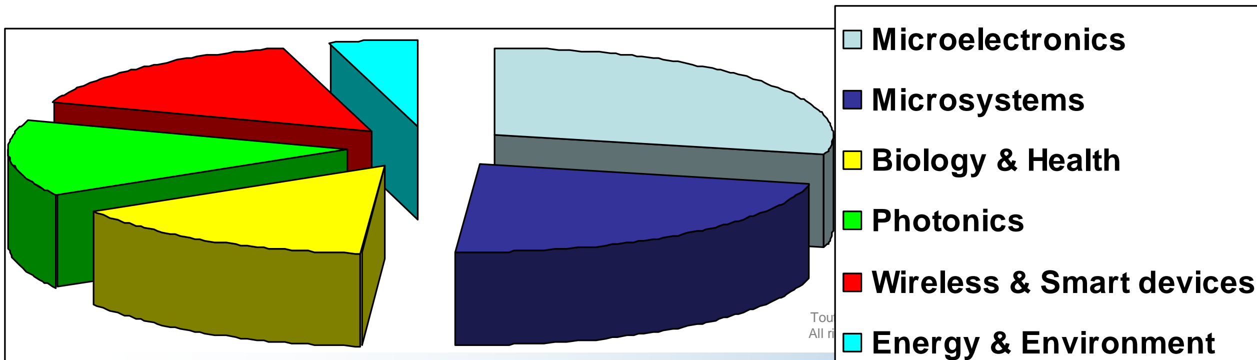
LETI in a few numbers - 2010

1 600 researchers
1 000 permanent LETI staff

300 M€ budget
> 73% from contract
~ 40 M€ CapEx

200 and 300mm Si capabities
8,000 m² clean rooms
Continuous operation

350 new patents in 2010
Portfolio > 1,500 patents
32 start-ups



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Since 2005: A complete set of research platforms…

CEA LETI (1600 CEA researchers)
collaborating
in MINATEC campus (3000 researchers)

MicroTechs for bio

200mm
'CMOS' new concepts
& Beyond CMOS

300mm
CMOS Integration
& adv. modules

Design

More Than Moore
200mm

Advanced Research
100-200mm

Nanoscale
Characterization

Incubation

Education

interacting daily with R & D platforms worldwide
(ST Crolles, IBM Albany, …)

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Micro/nano-Technologies

Micro Nano Technologies

Sciences de base

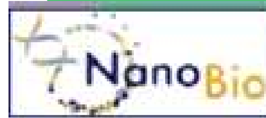
Basic research

Bio-Technologies

BioTechnologies

New Energy Technologies

Nouvelles Technologies pour l'Energie



Budget : 1 Billion€

with investment : 150 M€

10 000 researchers
10 000 students
> 5 000 publications/year
> 500 patents/year

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Outline

- Introduction : Trends and Hot Topics in Nanoelectronics
- Nanoelectronics scaling and use of the 3rd dimension to continue Moore's law.
- Interfacing the Multiphysics World (More Than Moore) thanks to functional diversification
- Building new systems and their packaging with a 3D tool box at a wafer level.
- Conclusions

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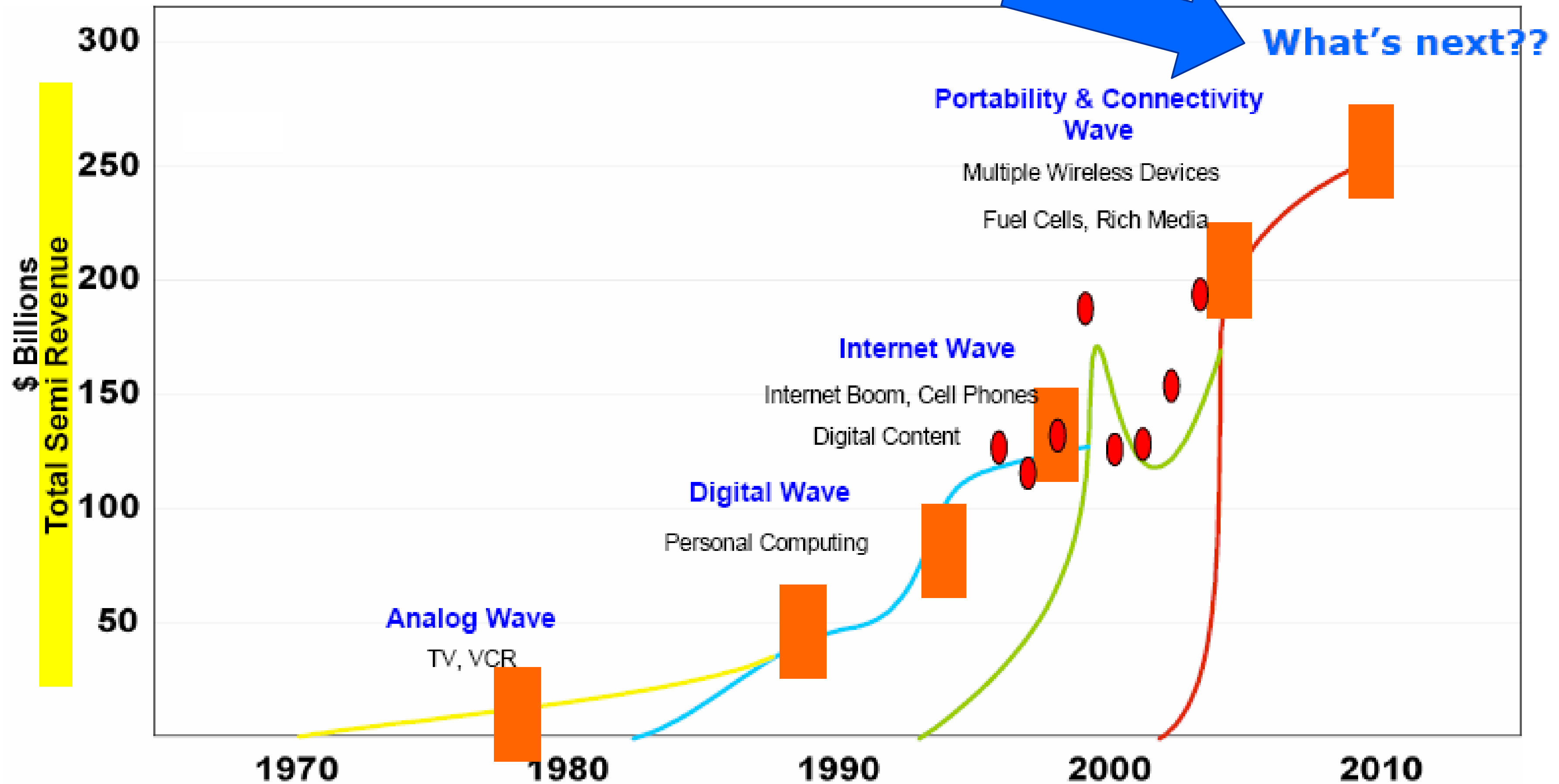
Semiconductor Market applications successive waves

Quality of life, Social, Environment, Health, Energy, …associated to ICT



Source : Semico Research Corp. May 2004 IPI Report

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Ecological Footprint of ICTs

reported by Intergovernmental Panel Climate Change(IPCC) *Source: TU Dresden*

- **Currently, 3 % of the world-wide energy is consumed by the ICT infrastructure**
  - which causes about 2 % of the world-wide CO2 emissions
  - comparable to the world-wide CO2 emissions by airplanes or ¼ of the world-wide CO2 emissions by cars
- **ICT: 10% of electrical energy in industrialized nations**
  - 900 Bill.. kWh / year = Central and South Americas
- **The transmitted data volume increases approximately by a factor of 10 every 5 years**

For ICTs, keep in mind:

$P = P_{stat} + P_{dyn}$ $P_{stat} = V_{dd} x I_{off}$ and $P_{dyn} = C V_{dd}^2 f$

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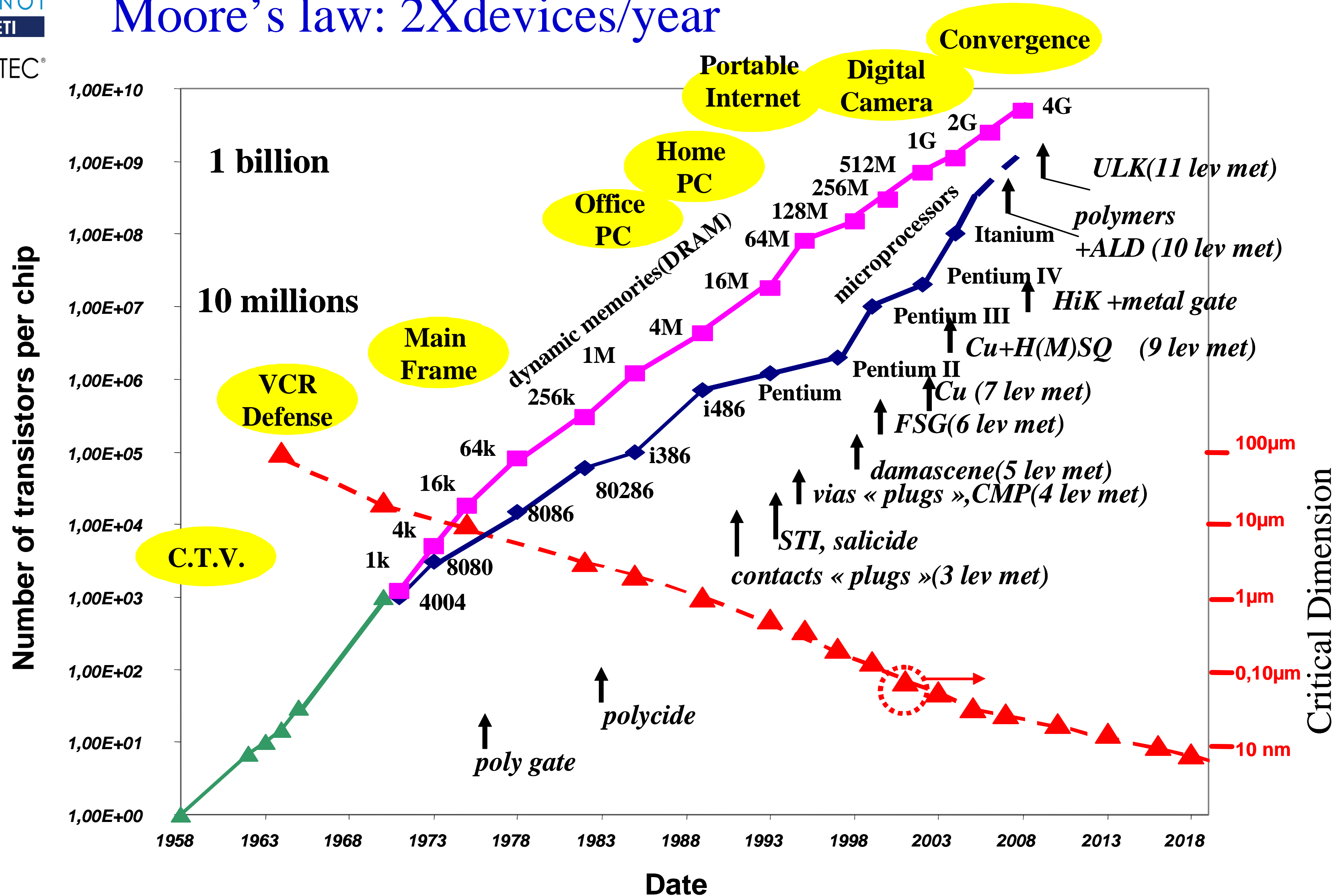
Scaling: a success story…thanks to innovation



Electronic Device Architectures for the Nano-CMOS Era
From Ultimate CMOS Scaling to Beyond CMOS Devices
Editor: S.Deleonibus, Pan Stanford Publishing, Oct 2008

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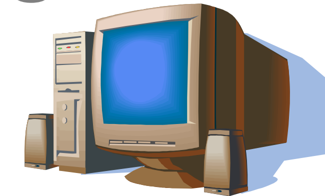
Nomadic consumer and professional products: largest market share continuously increasing

Three major product families

(ITRS aware of CMOS scaling limits)



- High Performance (HP) $t=CV/I$
  - Connection to power network

- Low Operating Power (LOP)
  - Intermittent Nomadic Function

- Low Stand-by Power (LSTP) $P_{stat} = V_{dd} \times I_{off}$
  - Permanent Nomadic Function

$$P_{dyn} = CV_{dd}^2 f$$

$$P_{tot} = P_{stat} + P_{dyn}$$

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EUV (λ = 13.5nm)

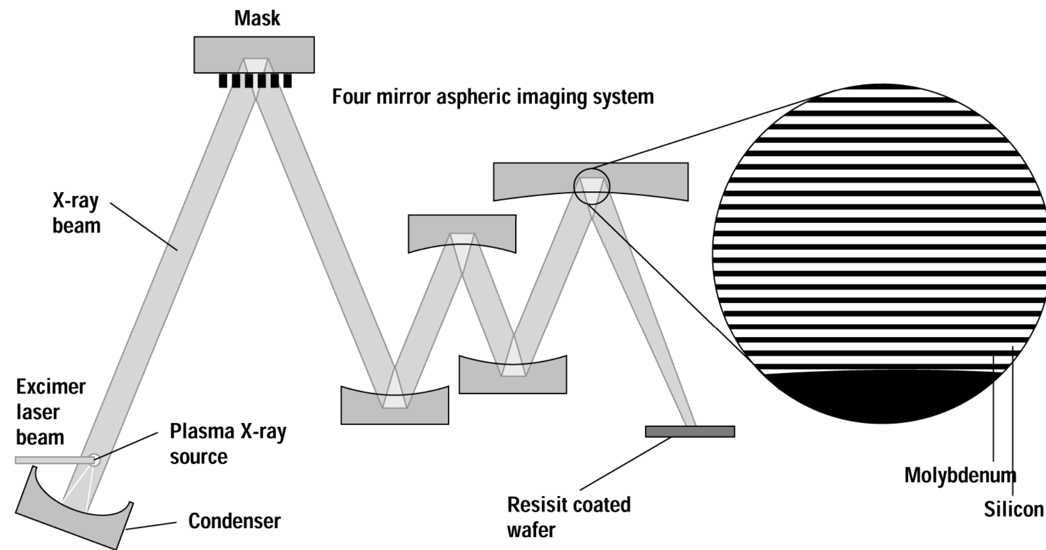

Figure 9.24 An x-ray projection lithography system using x-ray mirrors and a reflective mask *(after Zorpette, reprinted by permission, © 1992 IEEE).*

from S.A. Campbell, *The Science and Engineering of Microelectronic Fabrication*, Oxford University Press 2001

Engineering Test Stand (VNL/EUV-LLC)

- **60% reflectivity for several hundreds of Si / Mo stacks w roughness precision < 3Å**
- **Placement of mirror and mask**
- **Photoresist**

80-100 M$

100Wph !!

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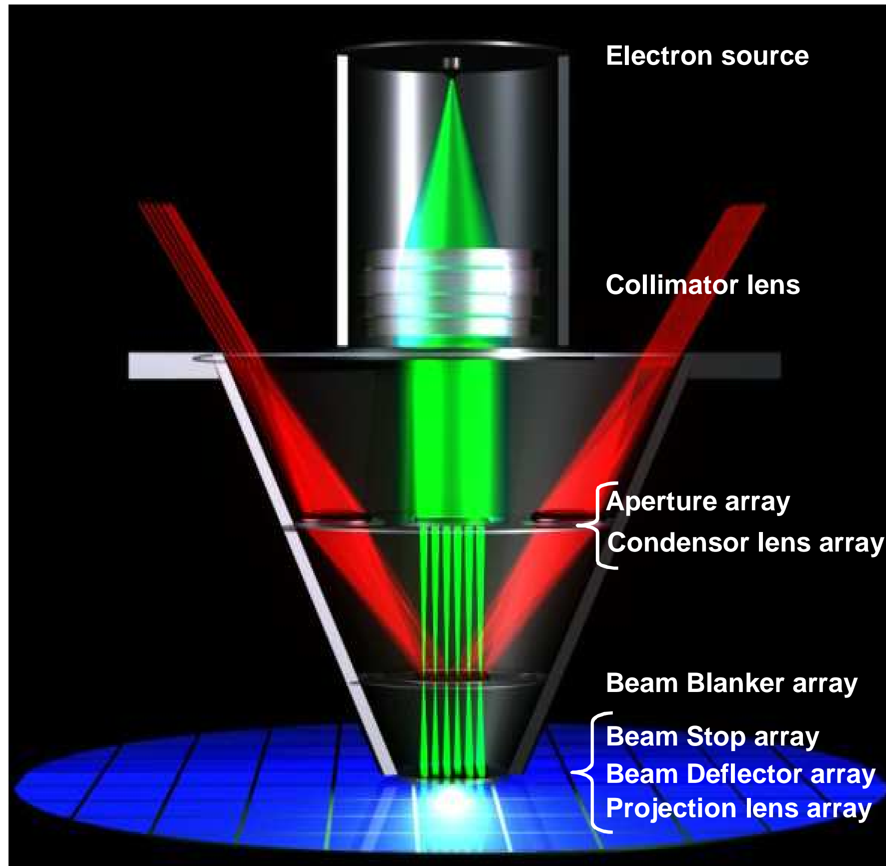
System made of 13,000 electron beams working in parallel (MAPPER) (1)



Key numbers 22nm node:

	HVM	pre-alpha
#beams and data channels	13,000	110
Spotsize:	25 nm	35 nm
Beam current:	13 nA	0.3 nA
Datarate/channel	3.5 Gbs	20 MHz
Acceleration voltage	5 kV	5 kV
Nominal dose	30 μC/cm^2	30 μC/cm^2
Throughput @ nominal dose	10 wph	0.002 wph
Pixel size @ nominal dose	3.5nm	2.25 nm
Wafer movement	Scanning	Static

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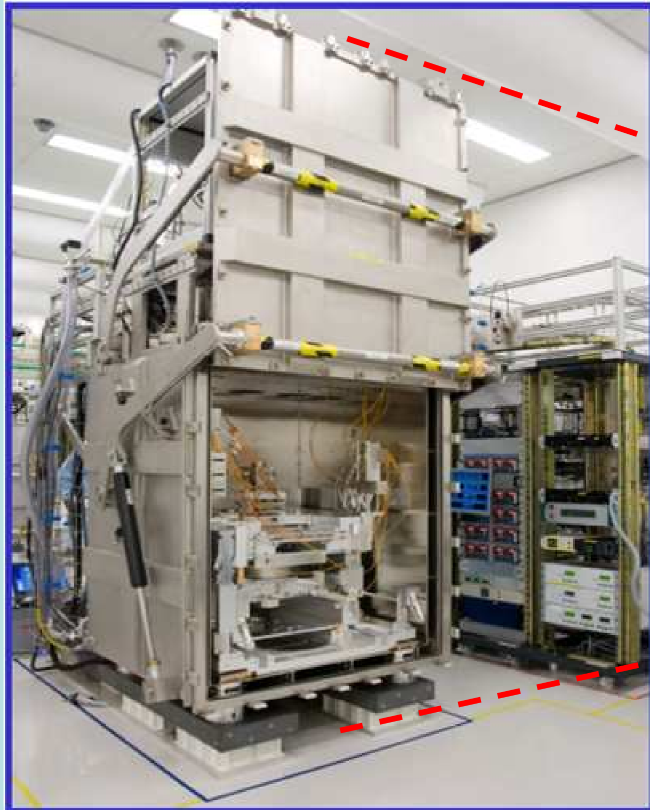
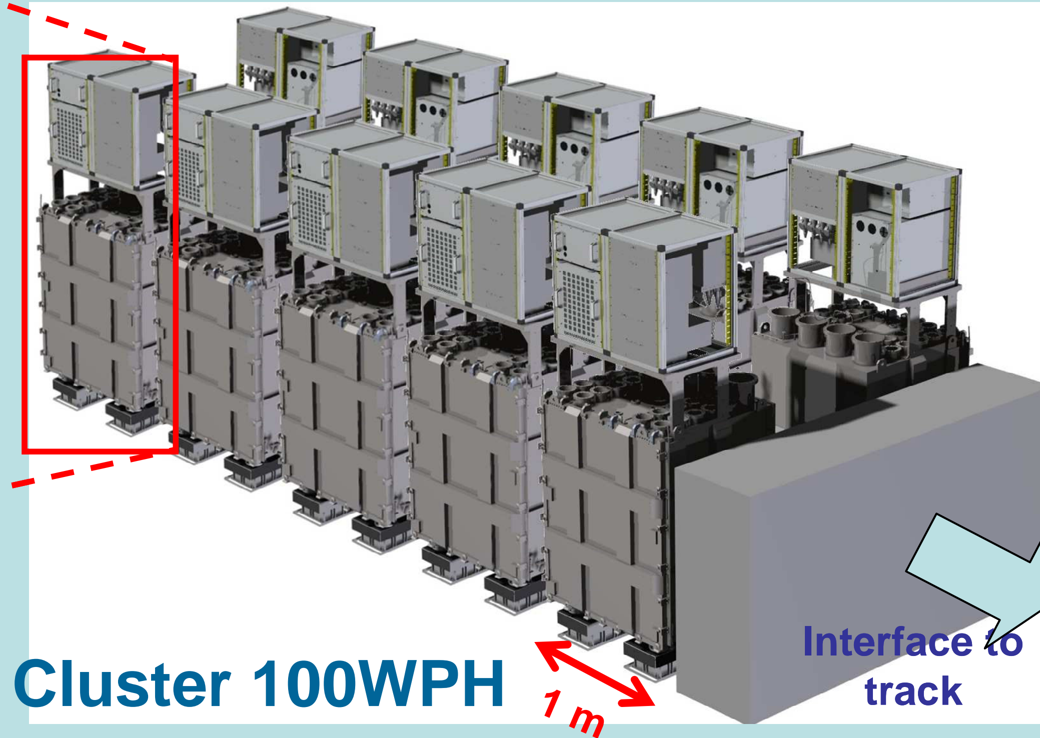
System made of 13,000 electron beams working in parallel (MAPPER) (2)



MAPPER single column tool. Upgrade to 13,000 beam for 10WPH



Cluster 100WPH

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Hot Topics: parasitic effects in MOSFET technology

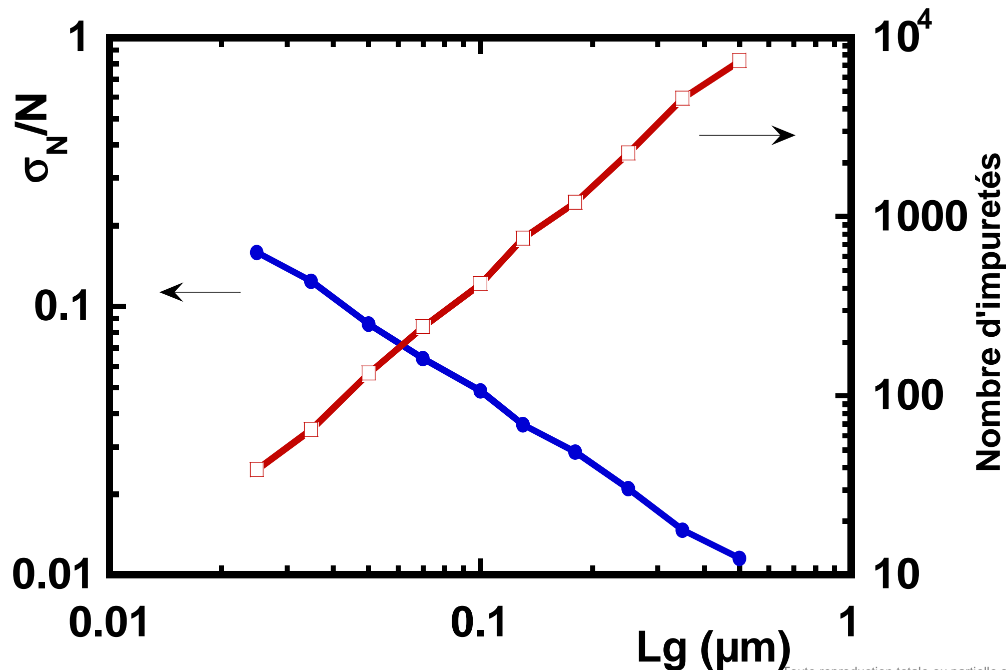
- Introduction of HiK and metal gate allows continued scaling and relaxes SiO2 gate leakage current related issues - Ig added to SCE, DIBL, subthreshold leakage(LETI IEDM 2002, Intel IEDM 2005)
- Statistical dopant variability

  - number of dopants in the active area decreases with scaling

  - random distribution of channel dopants

  Poisson's law. Standard deviation:

$$\sigma_{doping} = \left(\frac{N}{Volume} \right)^{1/2}$$



Statistical fluctuations of threshold voltage: 150 mV decay for VT=200mV(Lg=25nm) !!

Major interest for Low Doped channels

S.Deleonibus et al. ESSDERC 1999

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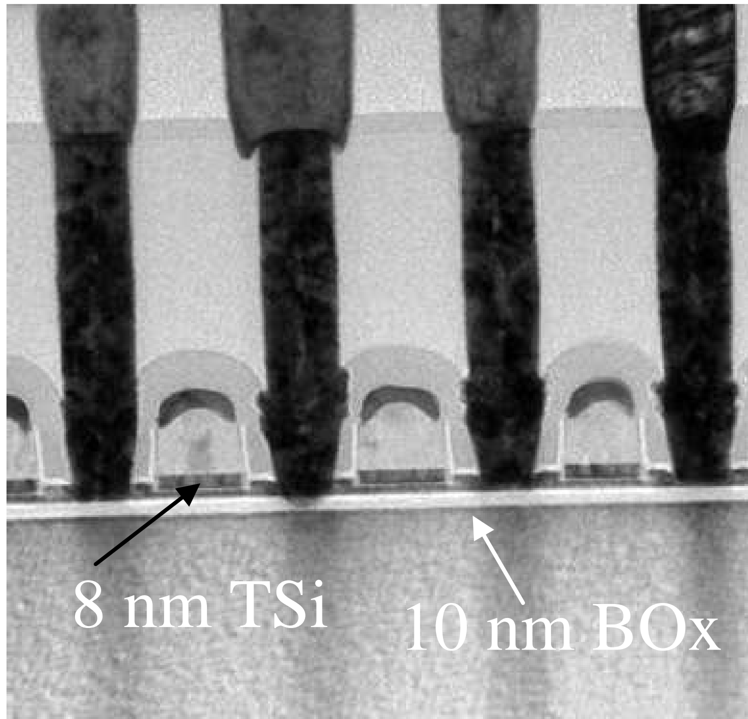
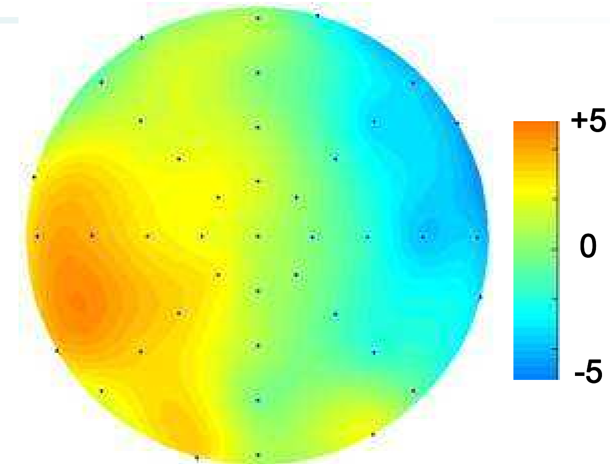
32nm Low Power FDSOI Undoped channels

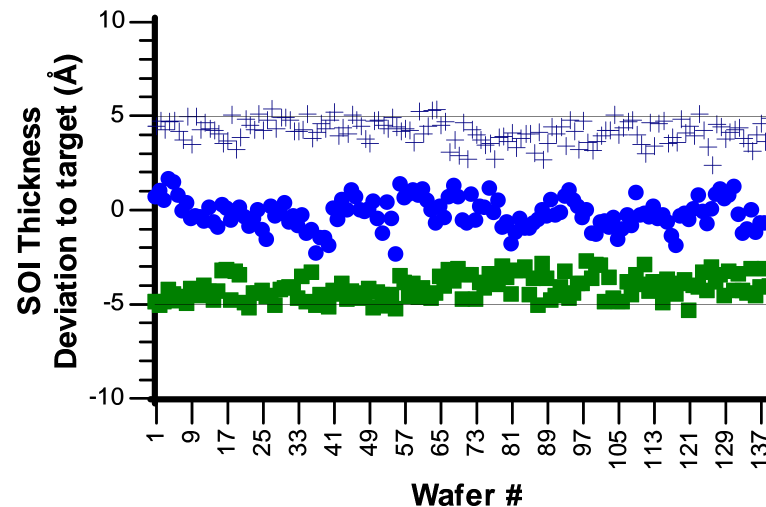
6T SRAM

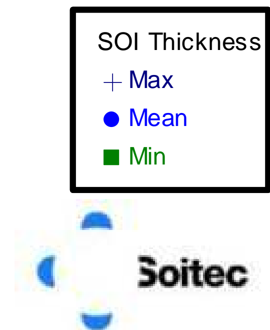
300mm wafers





Range = ±4 Å!





0.248µm² SNM (1.2V)=140mV

0.179µm² SNM (1.2V)=230mV

VDD=1V Ioff=6pA/µm

C.Fenouillet Beranger et al., IEDM 2007, VLSI Symp 2010

V.Barral et al., IEDM2007

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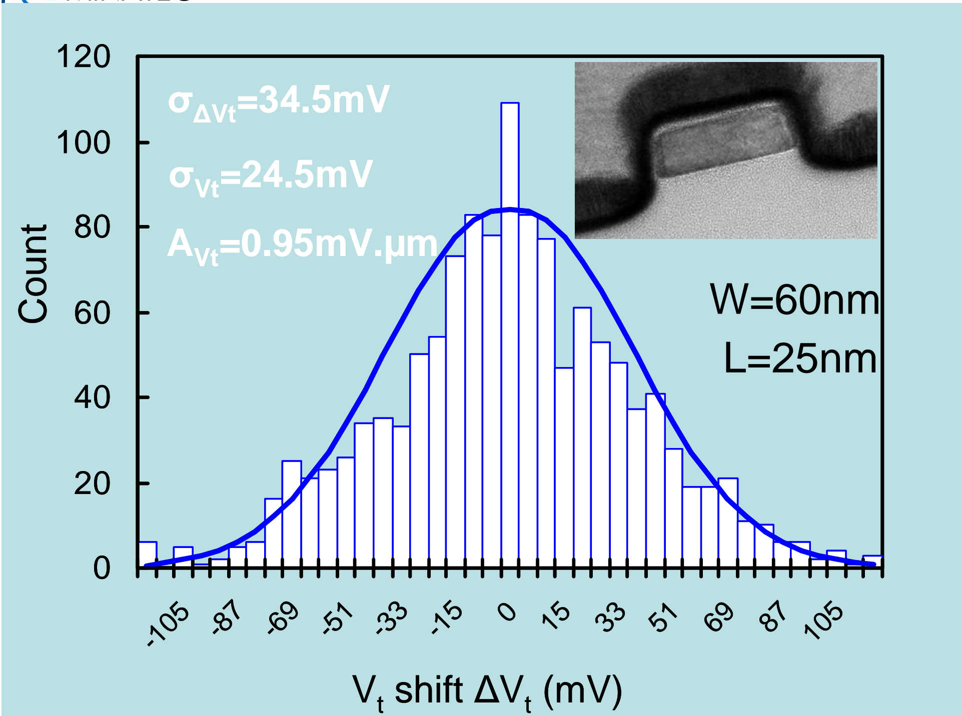
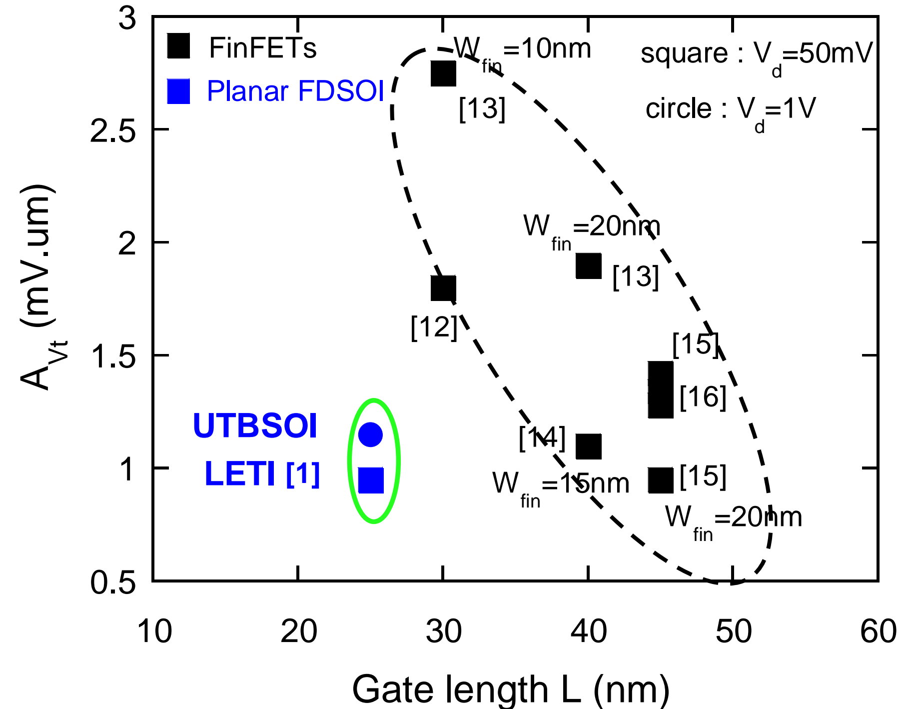
Record-high V_T matching performance

FDSOI Undoped channels vs.FinFET





O.Weber et al., IEDM 2008

$$\sigma_{Vt} = \frac{A_{Vt}}{\sqrt{WL}}$$

($\sigma_{Vt}=\sigma_{\Delta Vt}/\sqrt{2}$ to compare measurements on pairs and on arrays of transistors in the literature)

Best trade-off between V_T variations and gate length scaling compared to bulk MOSFETs and FinFETs

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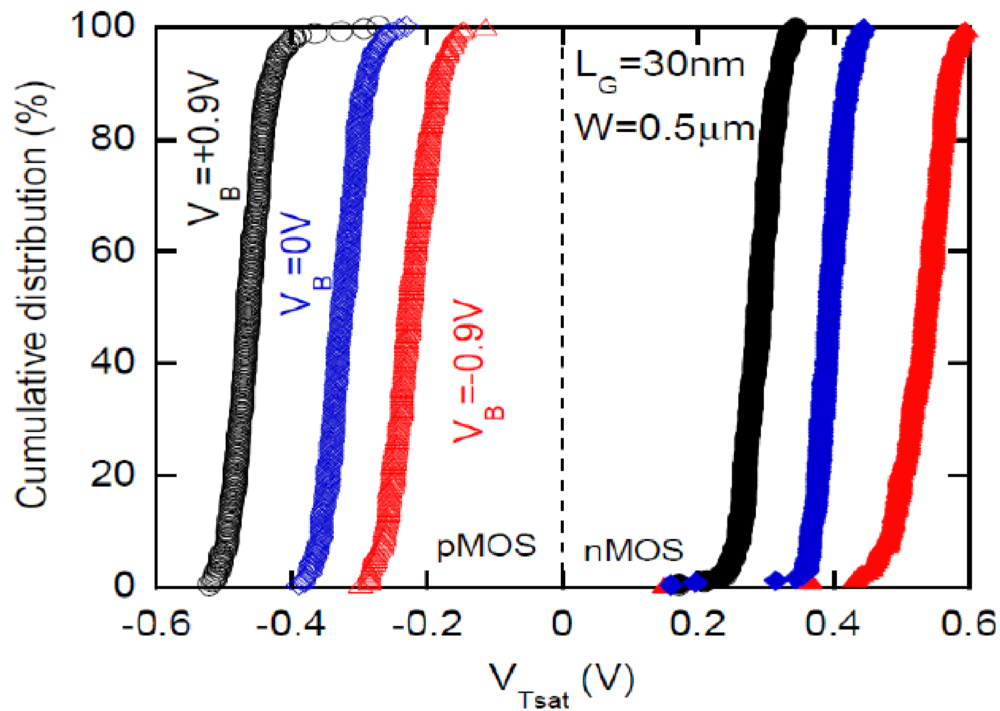
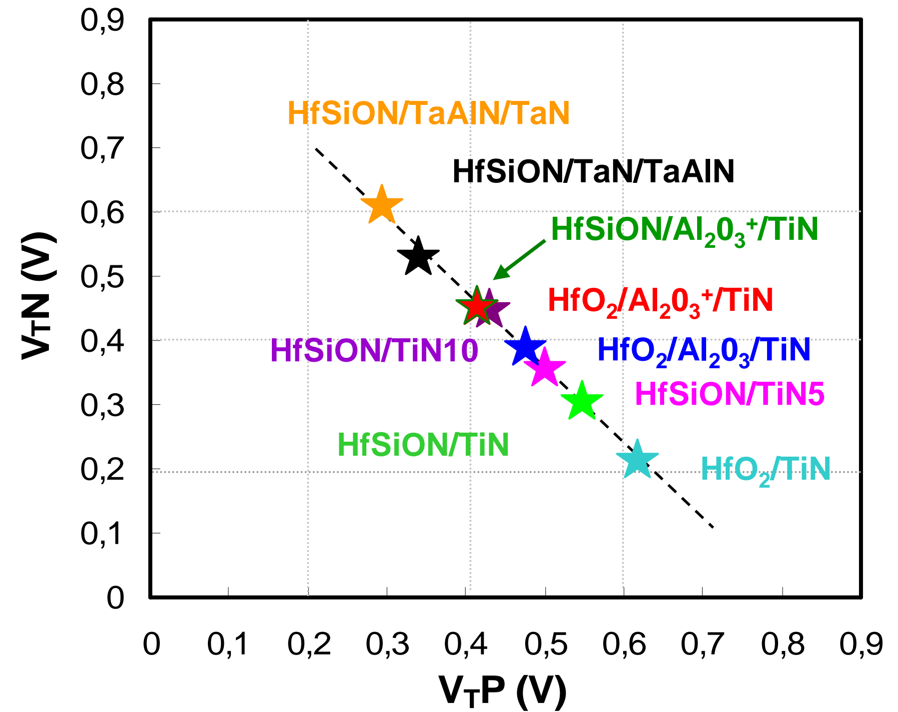
Multi VT solutions for SOC design

UTBOX + Back bias ; Gate stack engineering





BOX = 10nm and VBB/ Ground Plane
N and PMOS: VT modulation of ≤200mV

VT tuning by gate stack engineering

F.Andrieu et al. , VLSI 2010 Honolulu
O.Faynot et al., IEDM 2010 San Francisco, invited talk

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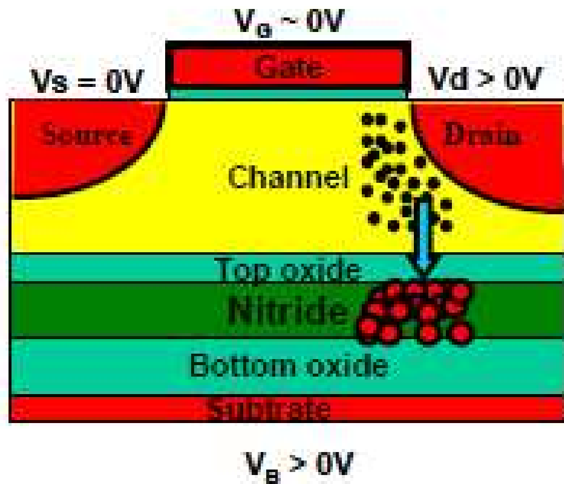
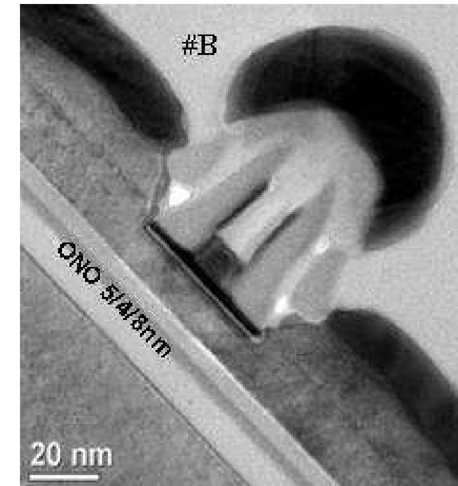
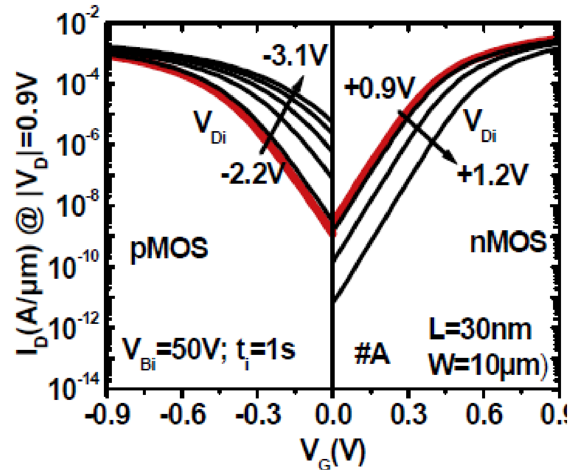
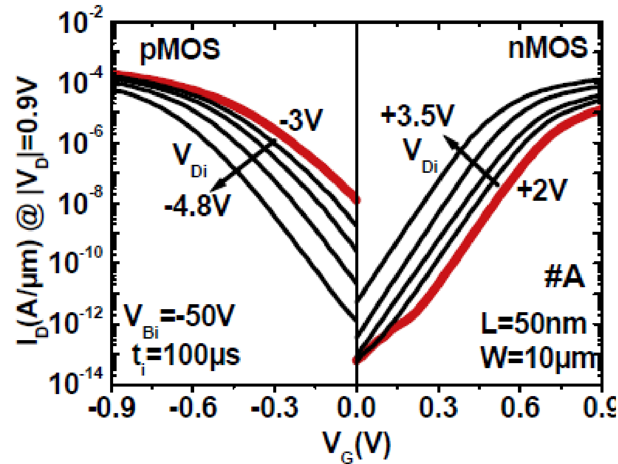
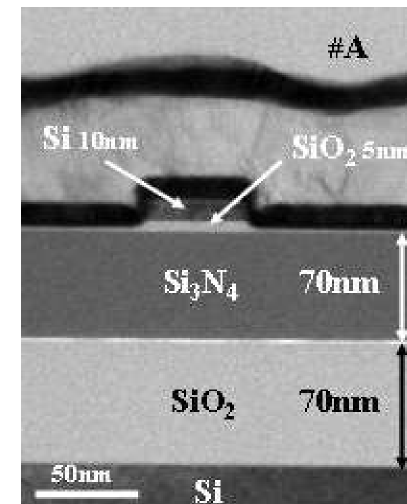
VT adjust by charge injection in BOx











P.Nguyen et al , VLSI Tech 2011

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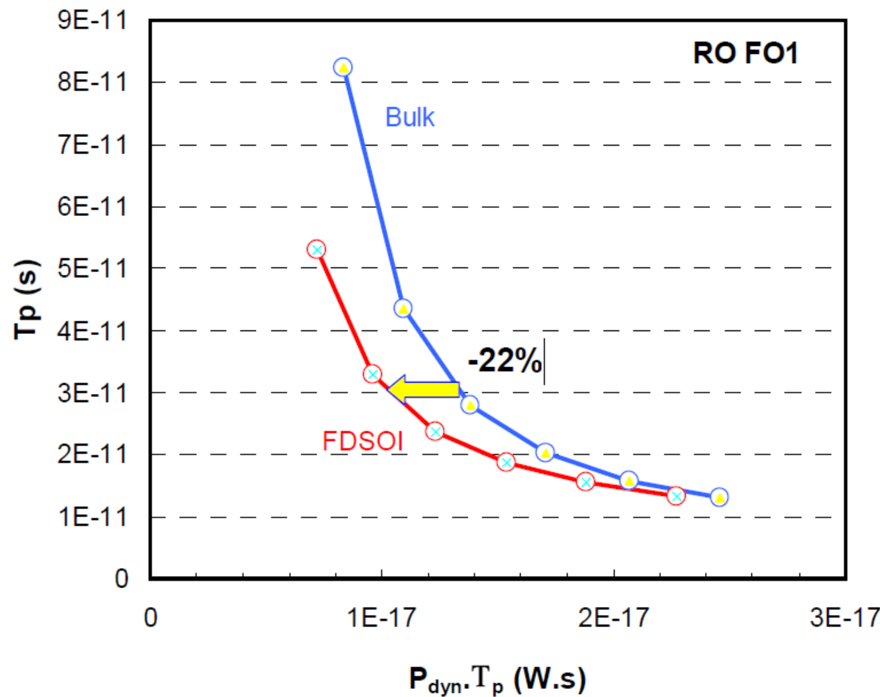
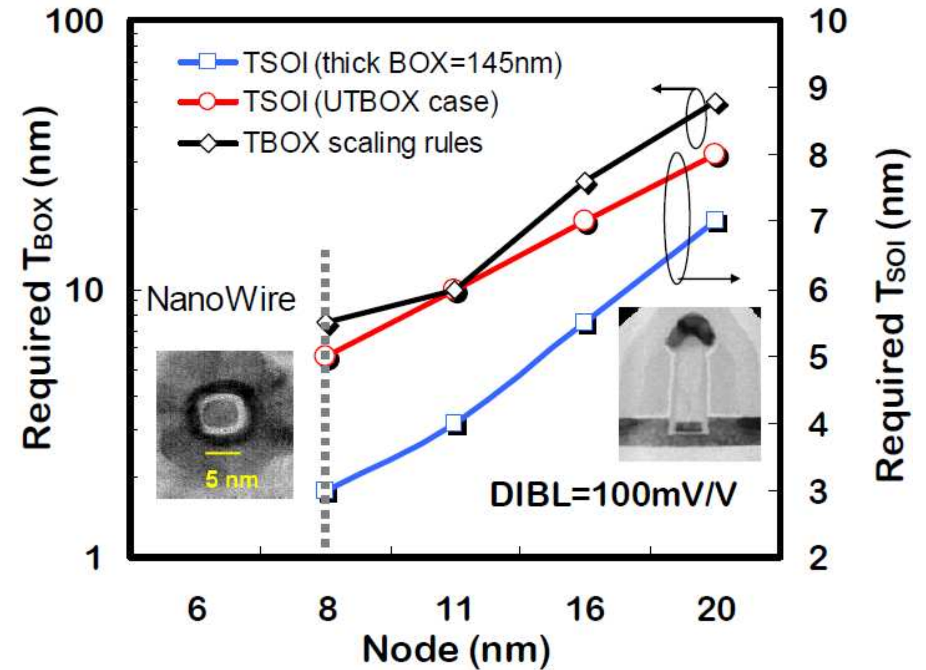
Merits of FDSOI

Delay vs. Power x Delay
22% improvement/bulk (20nm)



Reachable Scaling rules
(TSi, TBOx)



O.Faynot et al, IEDM 2010, invited talk

L.Clavelier et al, IEDM 2010, invited talk

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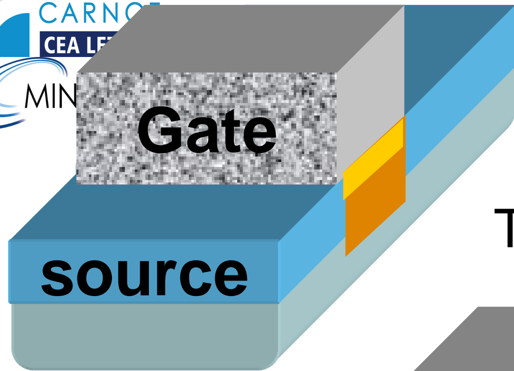
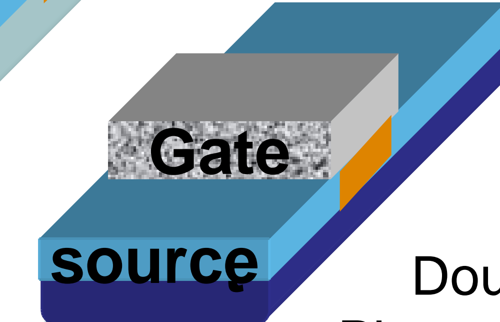
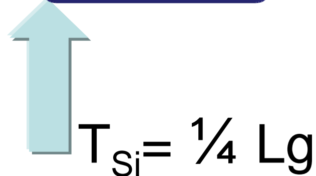
Bulk or thick SOI



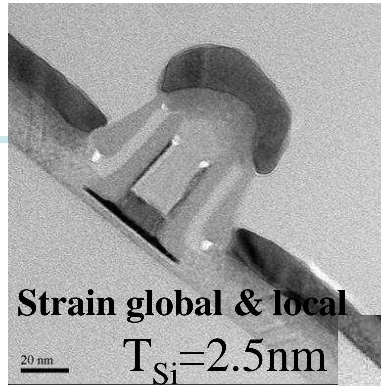
ThinSOI

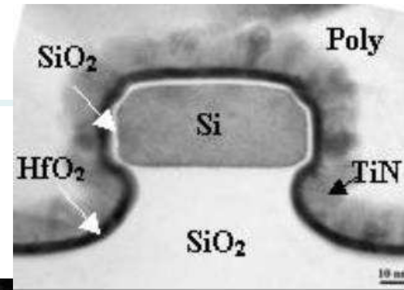


Planar

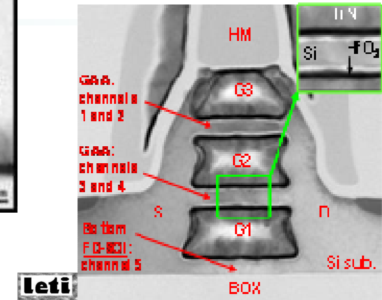


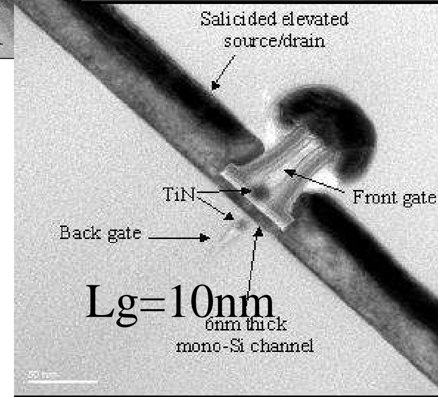
T_{Si}= ¼ Lg





Jahan et al. VLSI2005

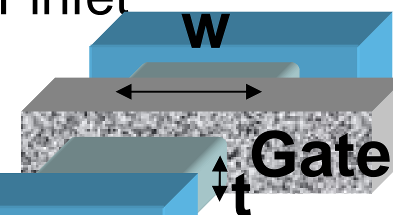




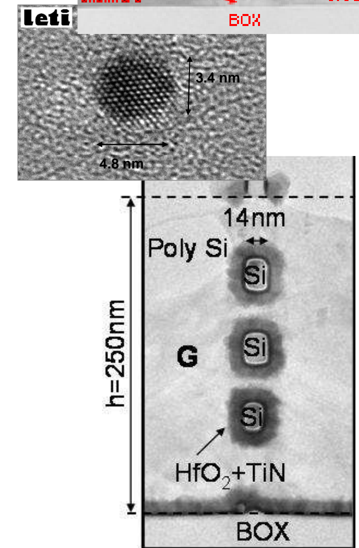
Barral et al. IEDM2007

Andrieu et al VLSI2006

Double-gate Planar or Finfet



Vinet et al. EDL 2005

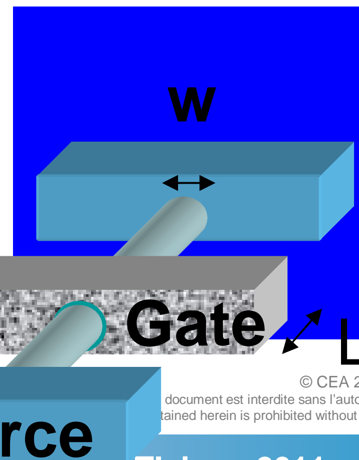


Thin Films Devices

Relaxing optimization scaling rule by architecture

T_{Si}= ½ Lg

Trigate/ nanowire



Bernard et al VLSI 2008

Dupré et al. IEDM 2008

Ernst et al. IEDM 2008

T_{Si}= 1 to 2 Lg

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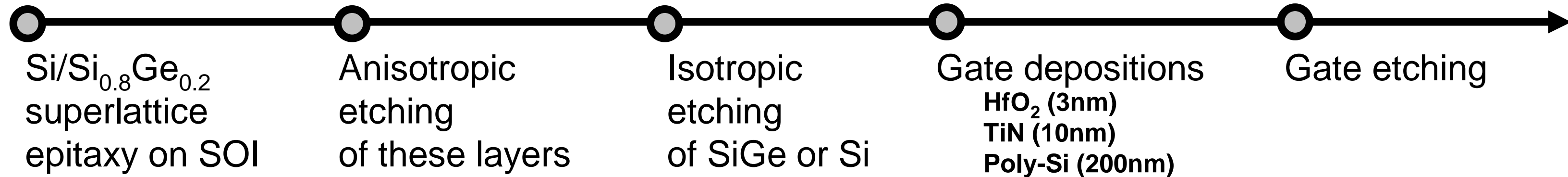
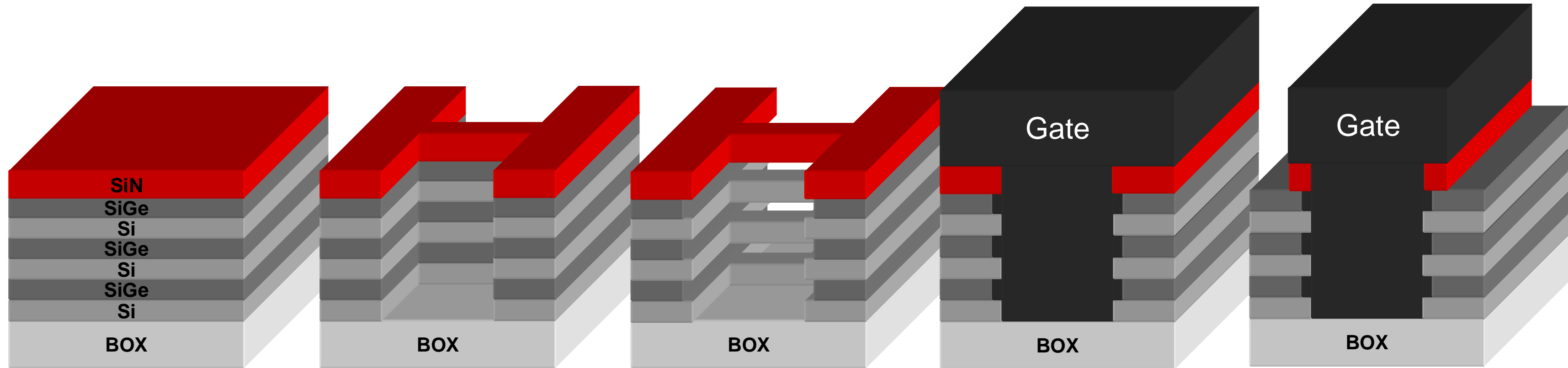
Device fabrication

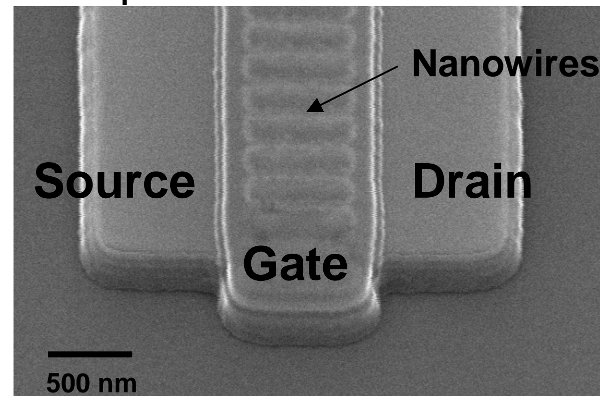




S/D implantation
Spacer formation
Activation anneal
Salicidation

Standard Back-End of-Line Processes

Top view of our device



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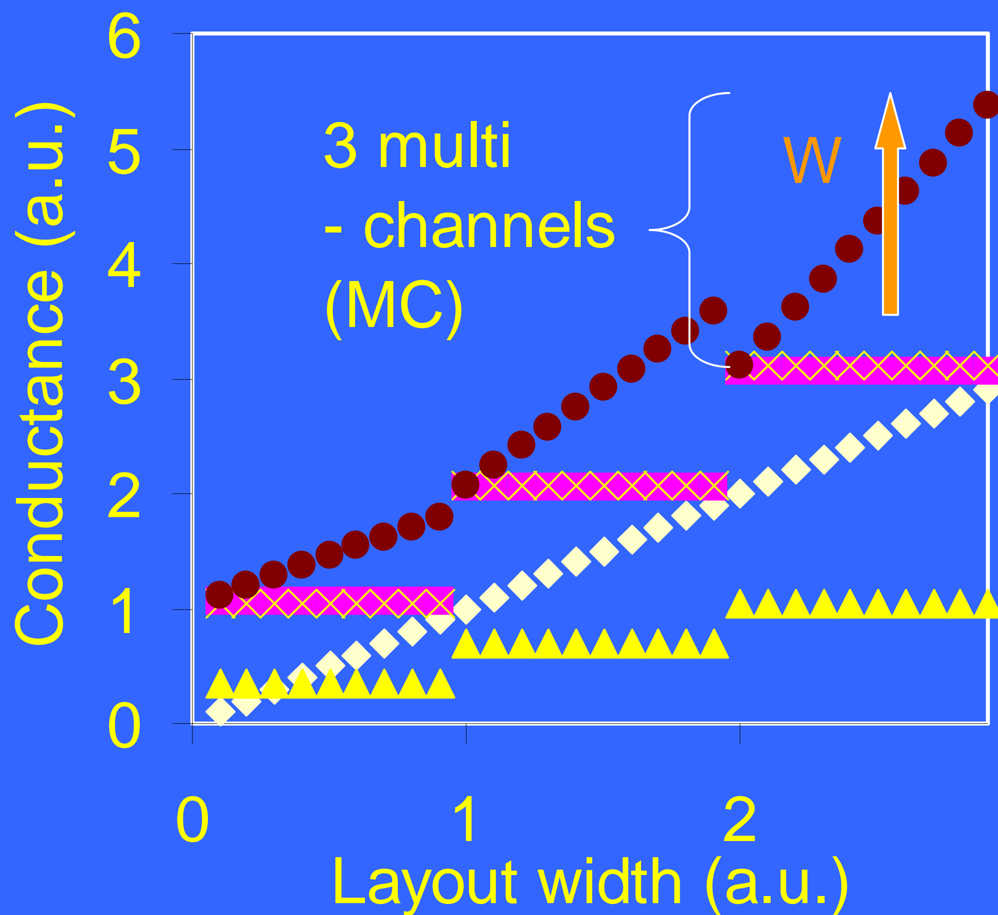
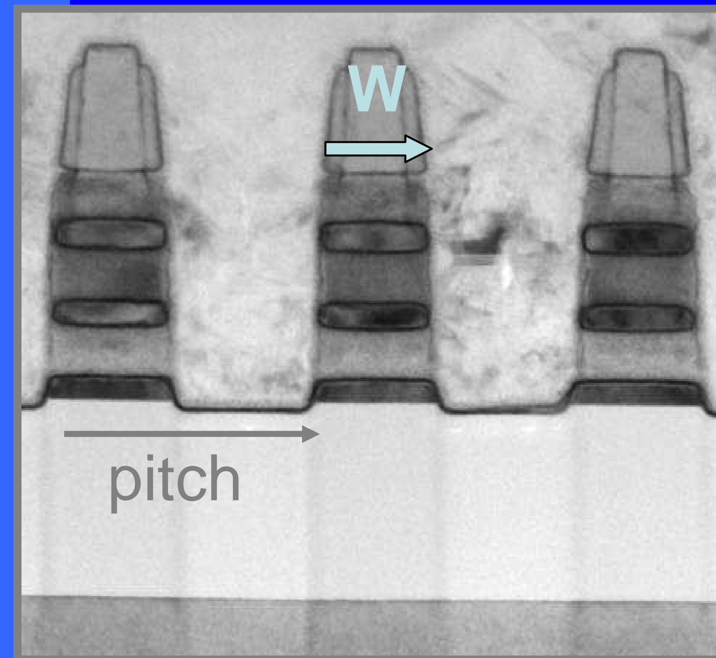
Tunable width

Design flexibility to tune the conductance





See for details:
T. Ernst et al, IEDM'06,'08 SSDM'07, ICIDT'08
E. Bernard et al. VLSI'08, ESSDER'07
C. Dupré et al, IEEE SOI Conference 07

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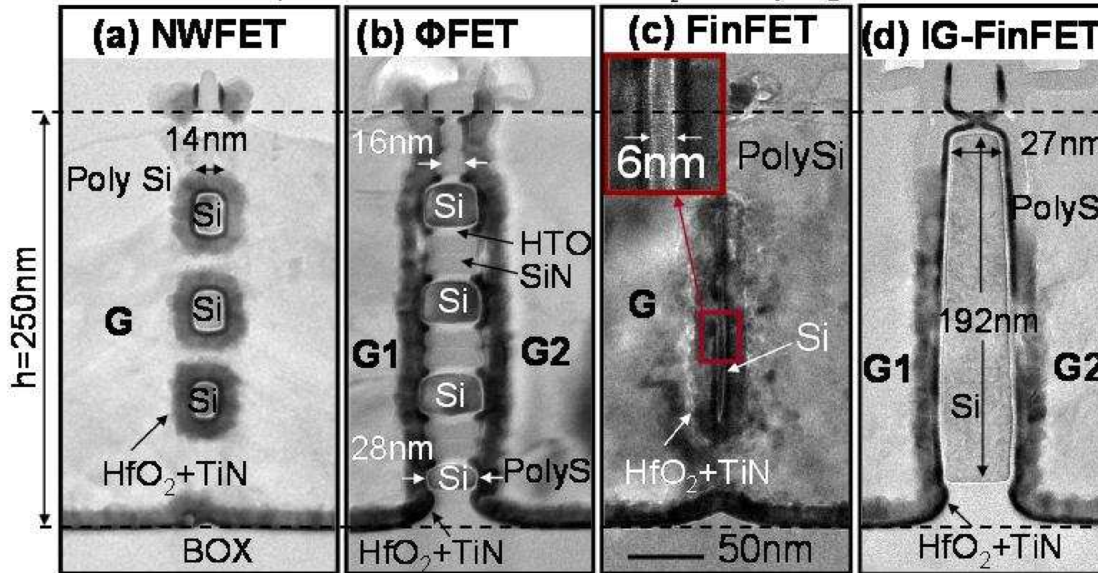
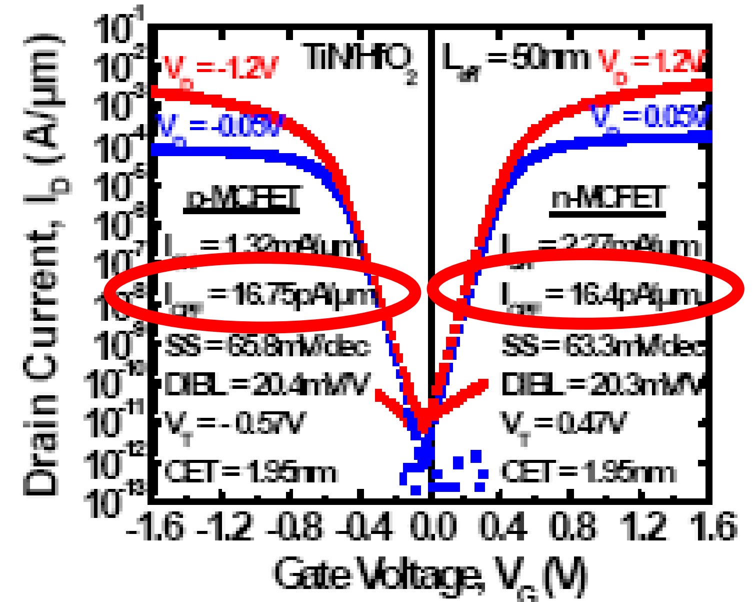
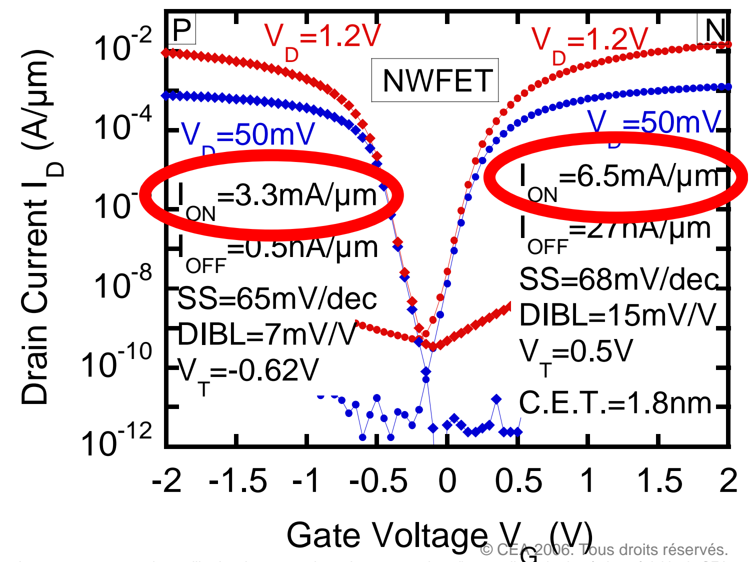
Stacked Multichannels and MultiNanowires

« Top-Down » approach







LETI top down approach for Low Power and High performance

- -CV/I outperforms Planar in loaded environment
- -Improved voltage gain (8GHz) wrt Planar
- -Gate separation possible
- -Transport properties in small nanowires

LETI: Dupré et al. IEDM 2008, San Francisco(CA)
Ernst et al., Invited talk IEDM 2008, San Francisco(CA)
Bernard et al, VLSI Symposium 2008 Honolulu
K.Tachi et al., IEDM 2010, San Francisco

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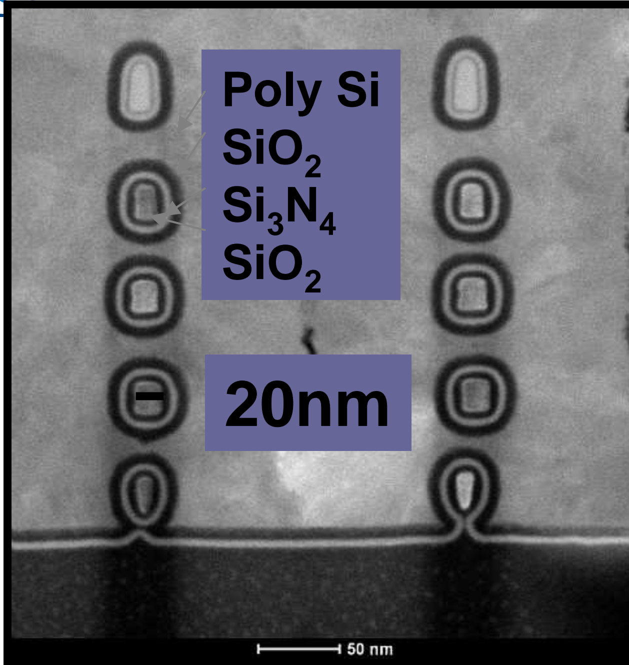
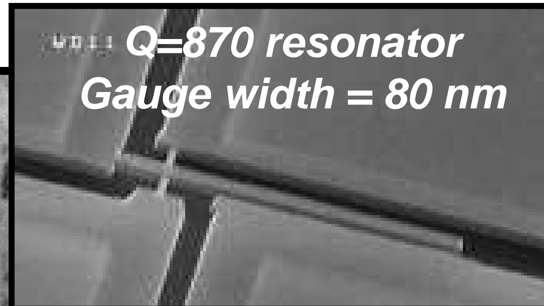
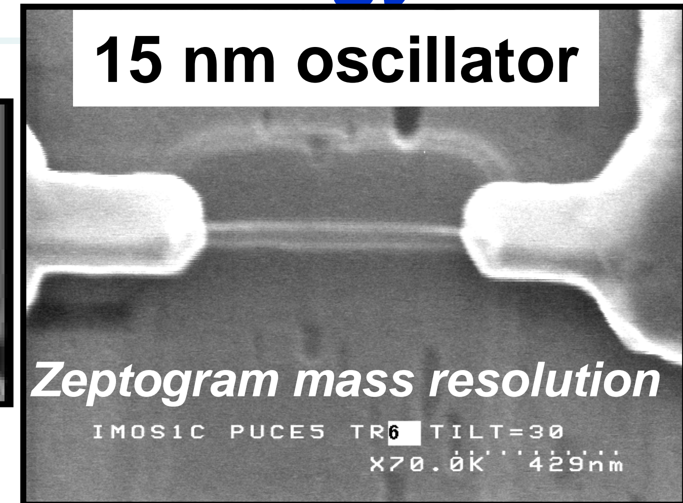
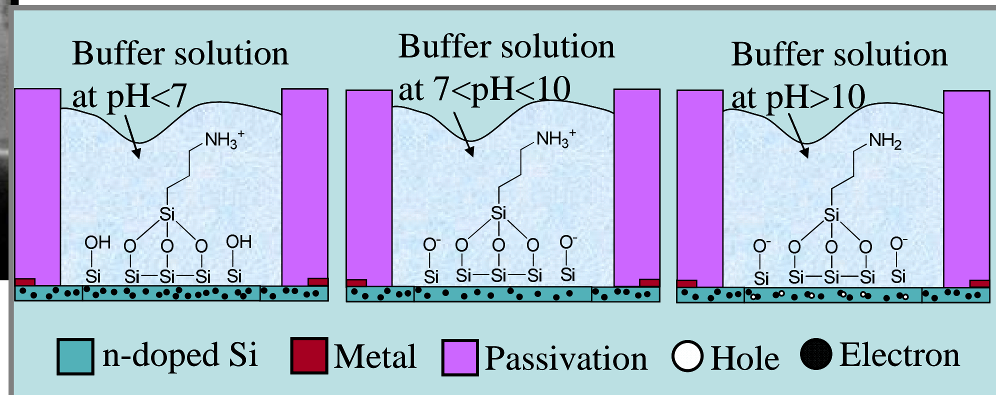
Pervasion of Nanowire technology

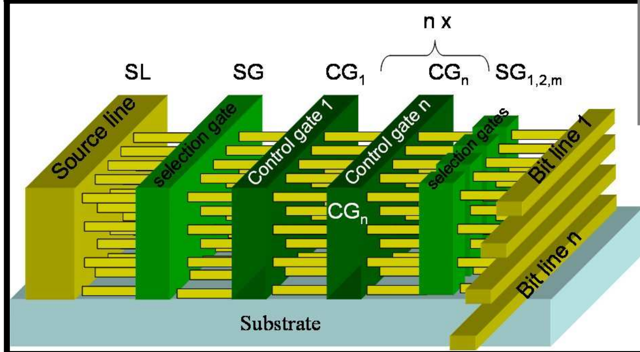
Mass detection



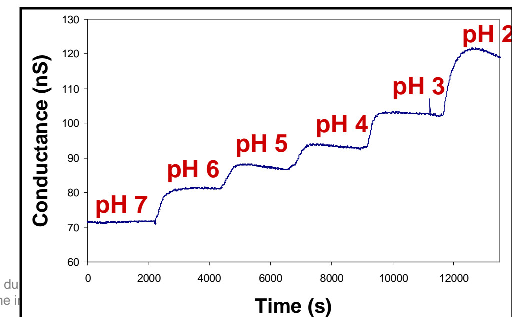








Chemical sensing



3D NAND Flash Memories

T.Ernst et al., IEDM 2008
Hubert et al., IEDM 2009

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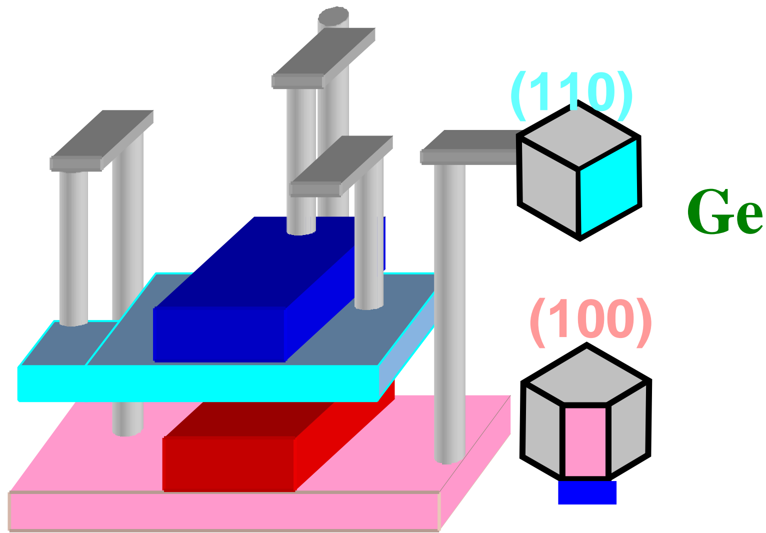
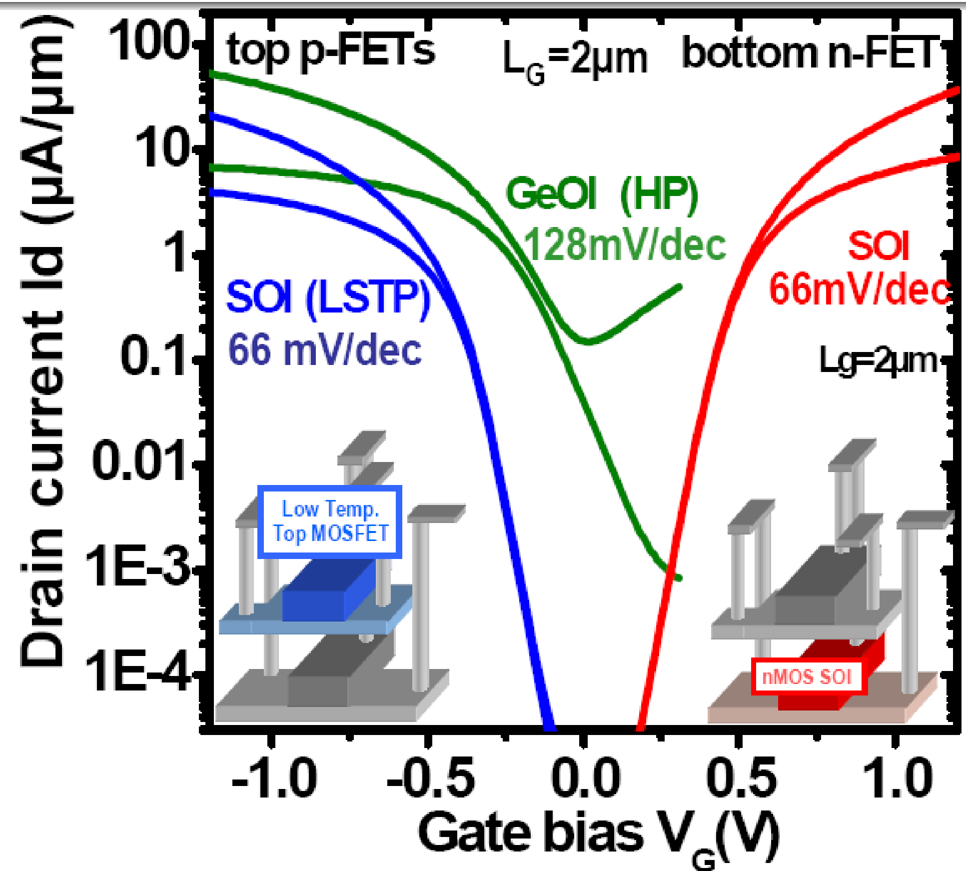
3D sequential process

Co-Integrating Heterogeneous orientation or materials





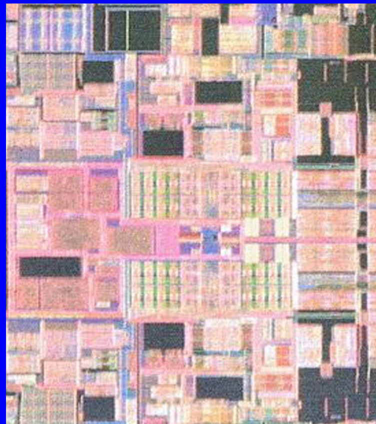
-4T SRAM
- cold end process(bonding).
Opportunities for other SC(Ge,III-V,...)
- improved layout (40% area SRAM cell)
-dynamically controlled VT:
improved RNM and SNM

P.Batude et al., Best student Paper Award, IEDM 2009

First heterogeneous orientation in 3D Si sequential integration
Enabled by use of wafer bonding by keeping low thermal budget

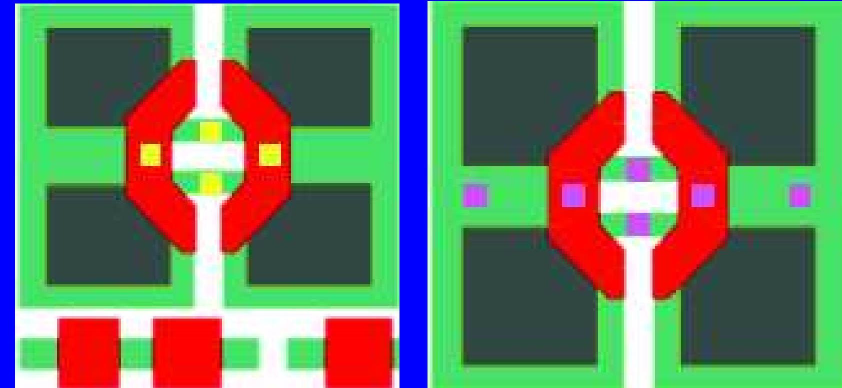
Sequential 3D: Potential and Demonstrated Applications

High density logic applications



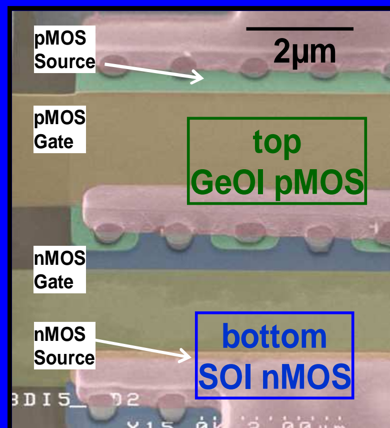
~ 1 node gain with same design rules for Front end levels

Highly miniaturized CMOS imagers pixels



P. Coudrain et al, IEDM 08,

Heterogeneous integration

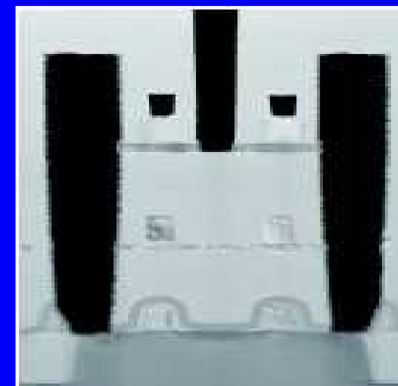


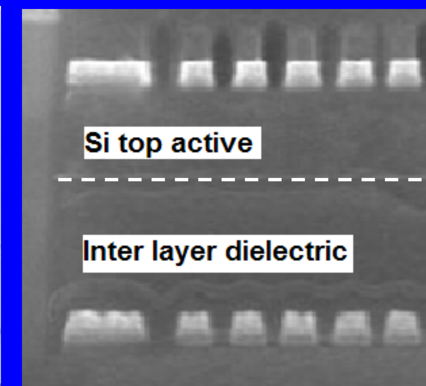
P. Batude et al,VLSI09

- Nanoelectronics & Photonics applications with Si-Ge Co-integration
- SRAM on top SOI logic, I/Os, analog on bottom bulk
- …

3D memories

- SRAMs
- FLASH

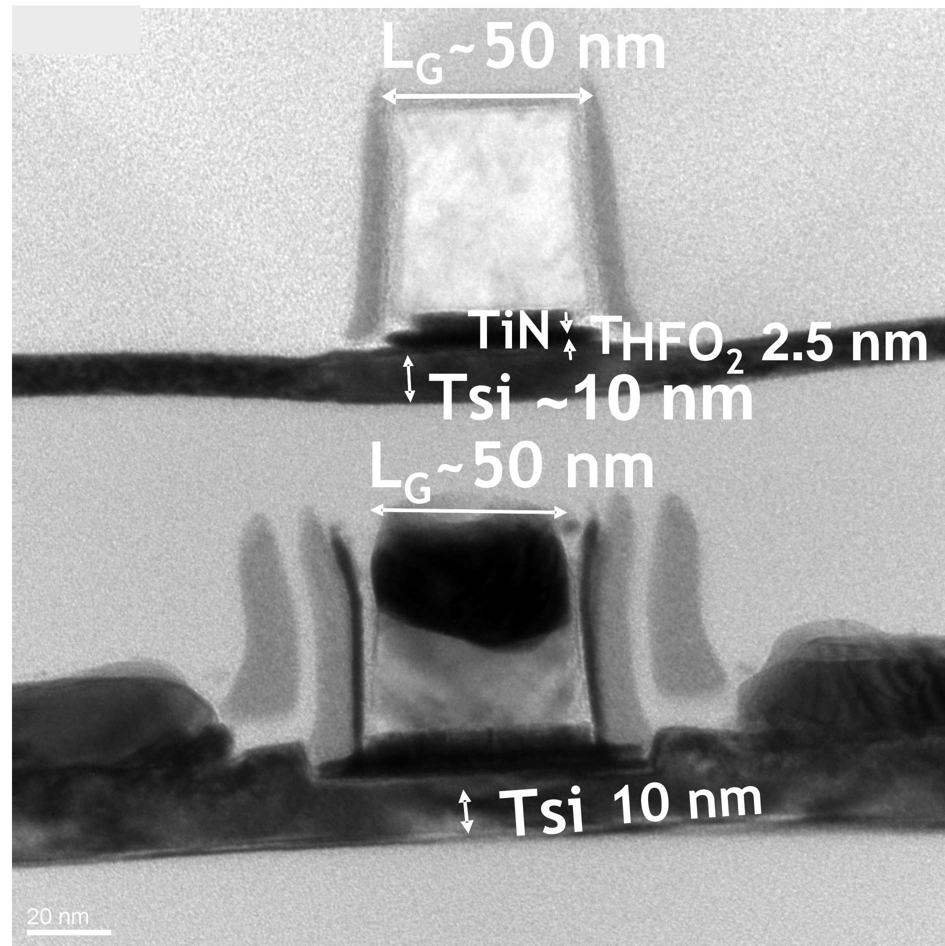




Y-H. Son et al, VLSI 07, Jung et al, IEDM 2006

P.Batude et al., IEDM 2009, Best Student Paper Award

Towards nanoscale devices



First demonstration of 3D sequential structure down to L_G 50 nm

P.Batude et al, 2011 VLSI Tech Symp

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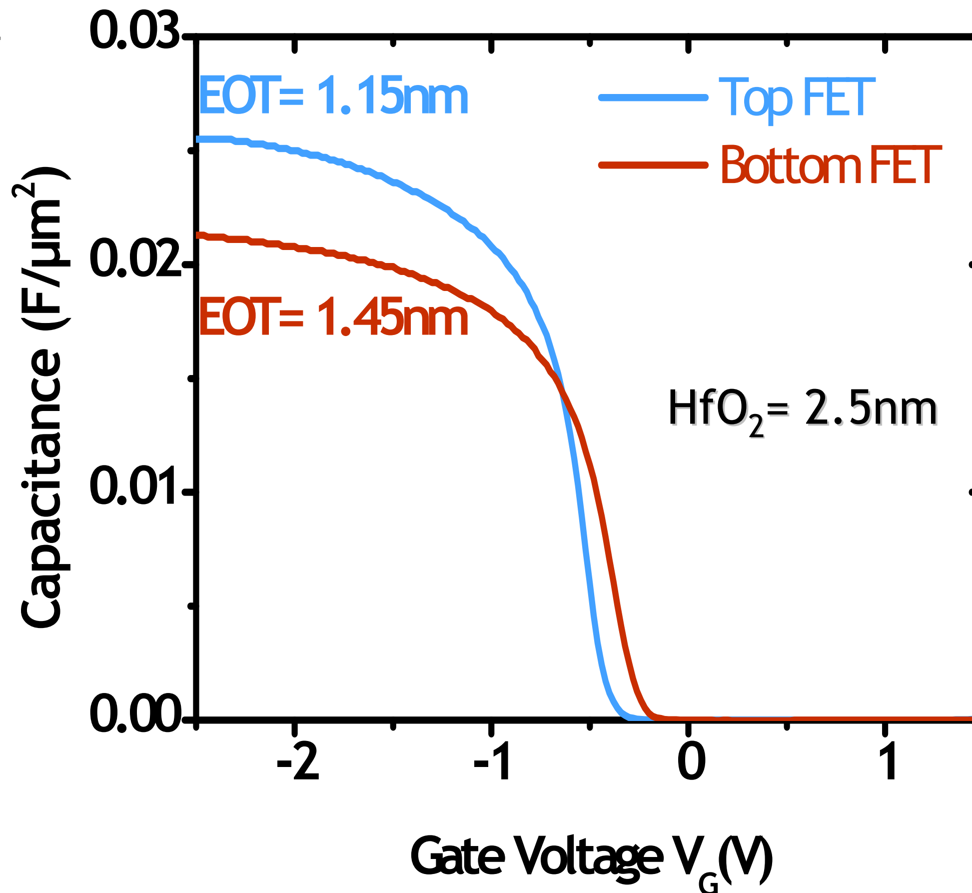
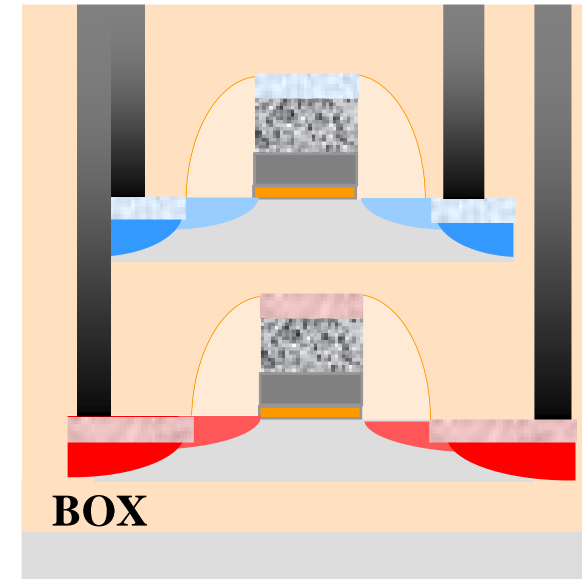
Specific interest of low temperature process





The low temp. process (600°C) leads to a reduced EOT
Explained by a reduction of interfacial oxide growth

P.Batude et al, 2011 VLSI Tech Symp

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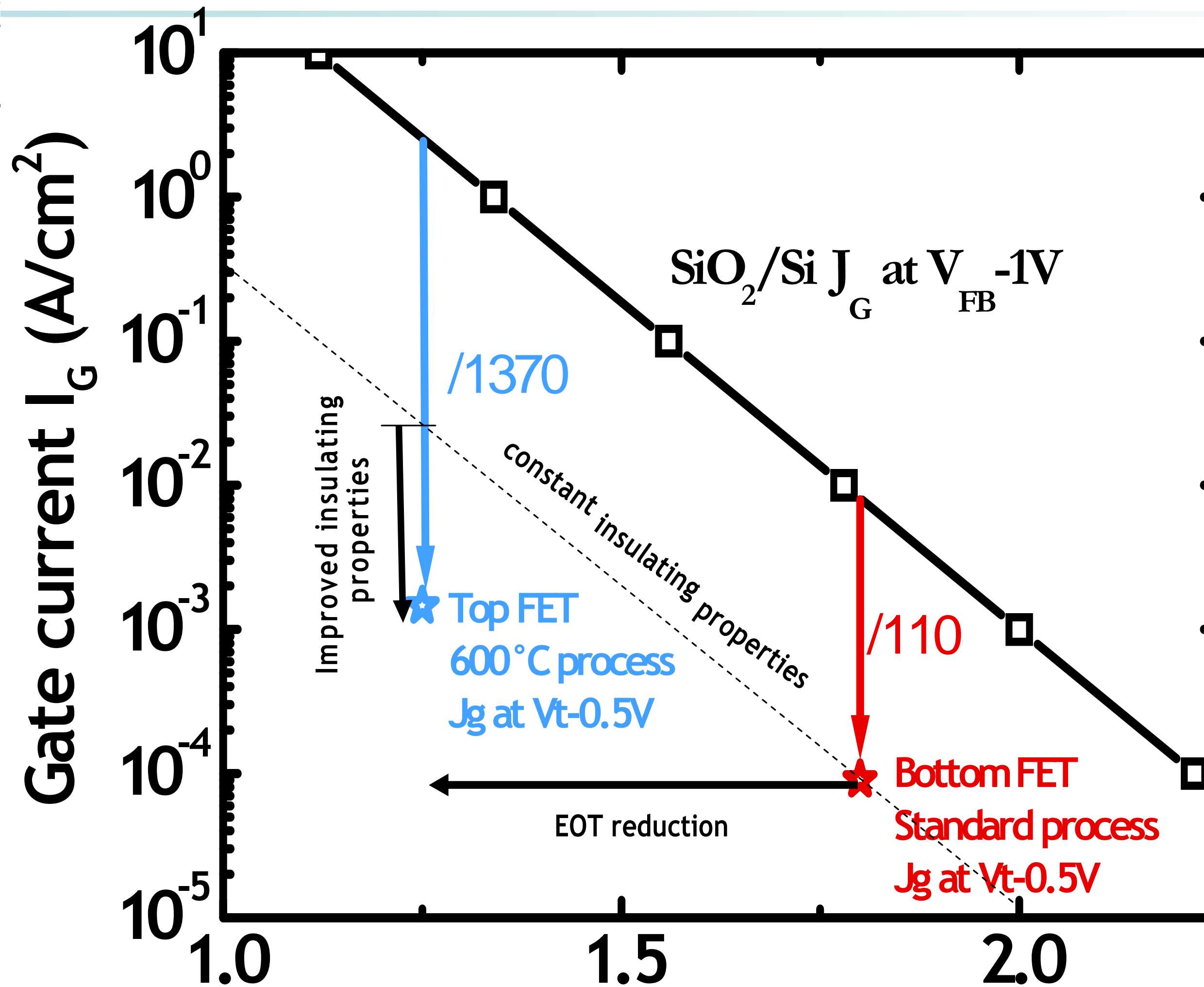
Specific interest of low temperature process



Improved insulating properties of low temperature stack

P.Batude et al, 2011 VLSI Tech Symp

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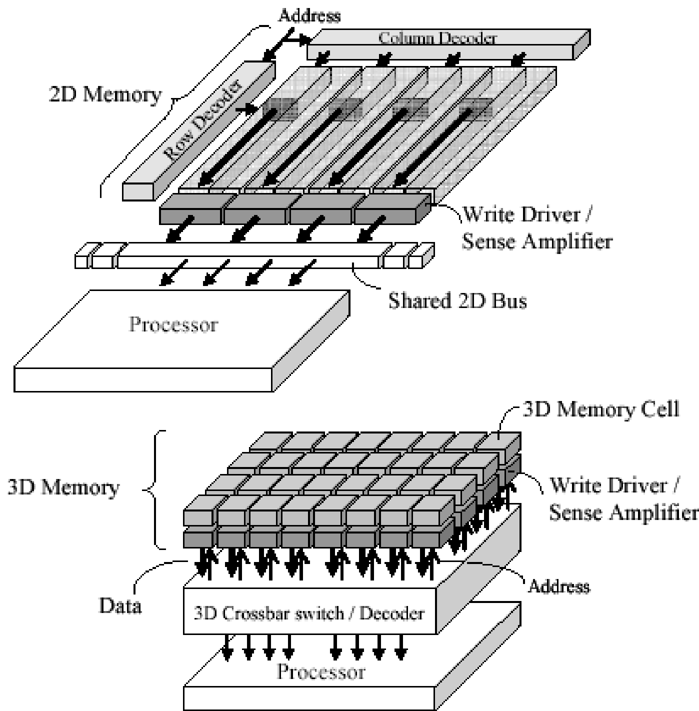
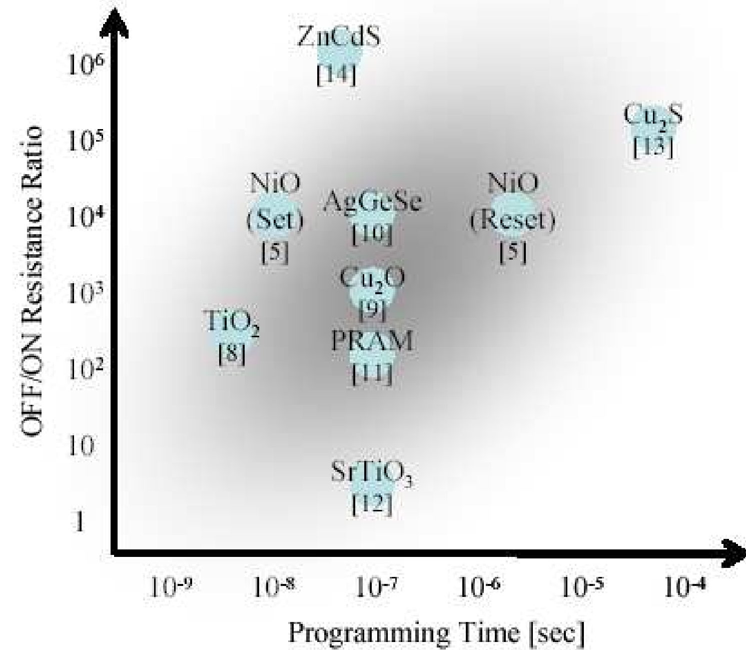
3D-Xbar Memory stacked on Logic: towards NV Logic





Resistive switches

Toshiba, Stanford Univ.: K.Abe et al, ICICDT 2008

Logic + Stacked NVM:
High bandwith,
Reduced Power consumption,…
Reconfigurability
ex: 32 nm node : > 1TB/s per 1mm^2

proven in 2D with
Magnetic Tunnel Junctions,
FeRAM ***Tohoku Univ., Hitachi:***
S.Matsunaga et al., Appl.Phys. Express(2008);
ROHM

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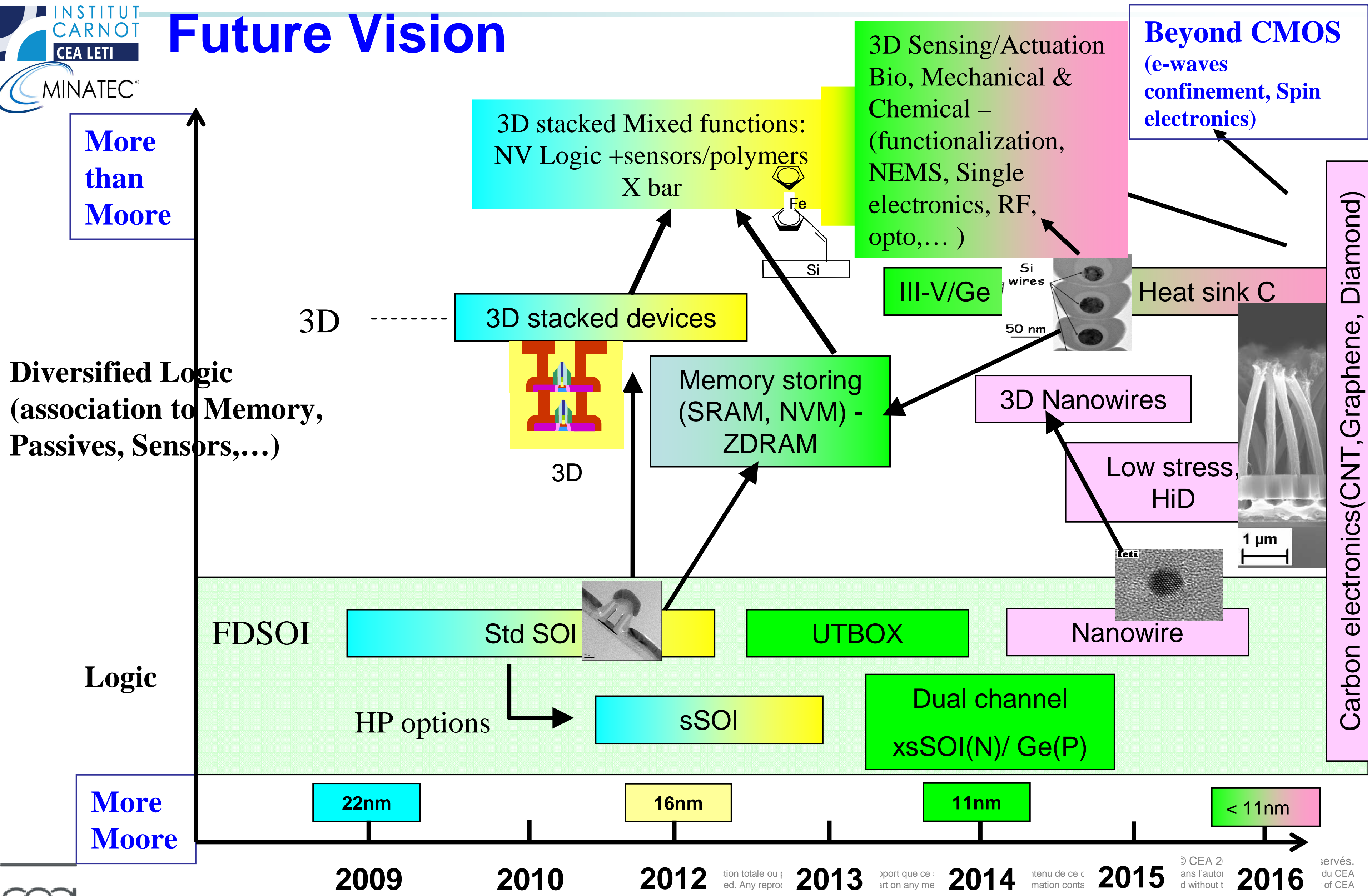
Advanced Devices and Systems Future Vision



Opportunities for other materials on Silicon

Electronic Device Architectures for the Nano-CMOS Era
From Ultimate CMOS Scaling to Beyond CMOS Devices
Editor: S.Deleonibus, Pan Stanford Publishing, July 2008

Material	μ_n ($cm^2V^{-1}s^{-1}$)	μ_p ($cm^2V^{-1}s^{-1}$)	s_{th} (W/m/K)	Rel. K	Eg(eV)	v_{sat}(10^7cm/s)	ni(cm^{-3}) $(m^*_e m^*_h/m^2)T^{3/2}$ exp(-Eg/2kT)
Si	1400	500	141	11.9	1.12	0,86	2×10^{10}
Ge	3900	1900	59.9	16	0.66	0,60	2×10^{13}
GaAs	8500	400	55	12.9	1.42	0.72	2.1×10^{6}
$InGa_{0.47}As_{0.53}$	12 000	300	5	13.9	0.74	0.6	6×10^{11}
InSb	77000	850	1.8	16.9	0.17	5.0 @77K	2×10^{16}
C-Diamond sp3	2200	1800	2000	5.7	5.47	2,7	10^{-27}
Graphene (CNT) sp2	10^4-10^5	10^4-10^5	1000	5.7	Semi-metal	4	$1 \times 10^{12} cm^{-2}$ (1×10^{15})

Well established high quality material (>40yrs experience) Oxidizable !

Silicon compatible
Available in all fabs
GaAs lattice constant matching

Opto/Power RF applications
Ge compatible
HP N channel

BTBT TFET/vW

Poor short channel effect immunity

Highest μ_n but Worst μ_n/μ_p!!

Passive layer combine w BOx (thermal shunt)

Highest σ_{th}

High short channel effect immunity

Most compact logic, Interconnect

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Outline

- Introduction : Trends and Hot Topics in Nanoelectronics
- Nanoelectronics scaling and use of the 3rd dimension to continue Moore's law.
- Interfacing the Multiphysics World (More Than Moore) thanks to functional diversification
- Building new systems and their packaging with a 3D tool box at a wafer level.
- Conclusions

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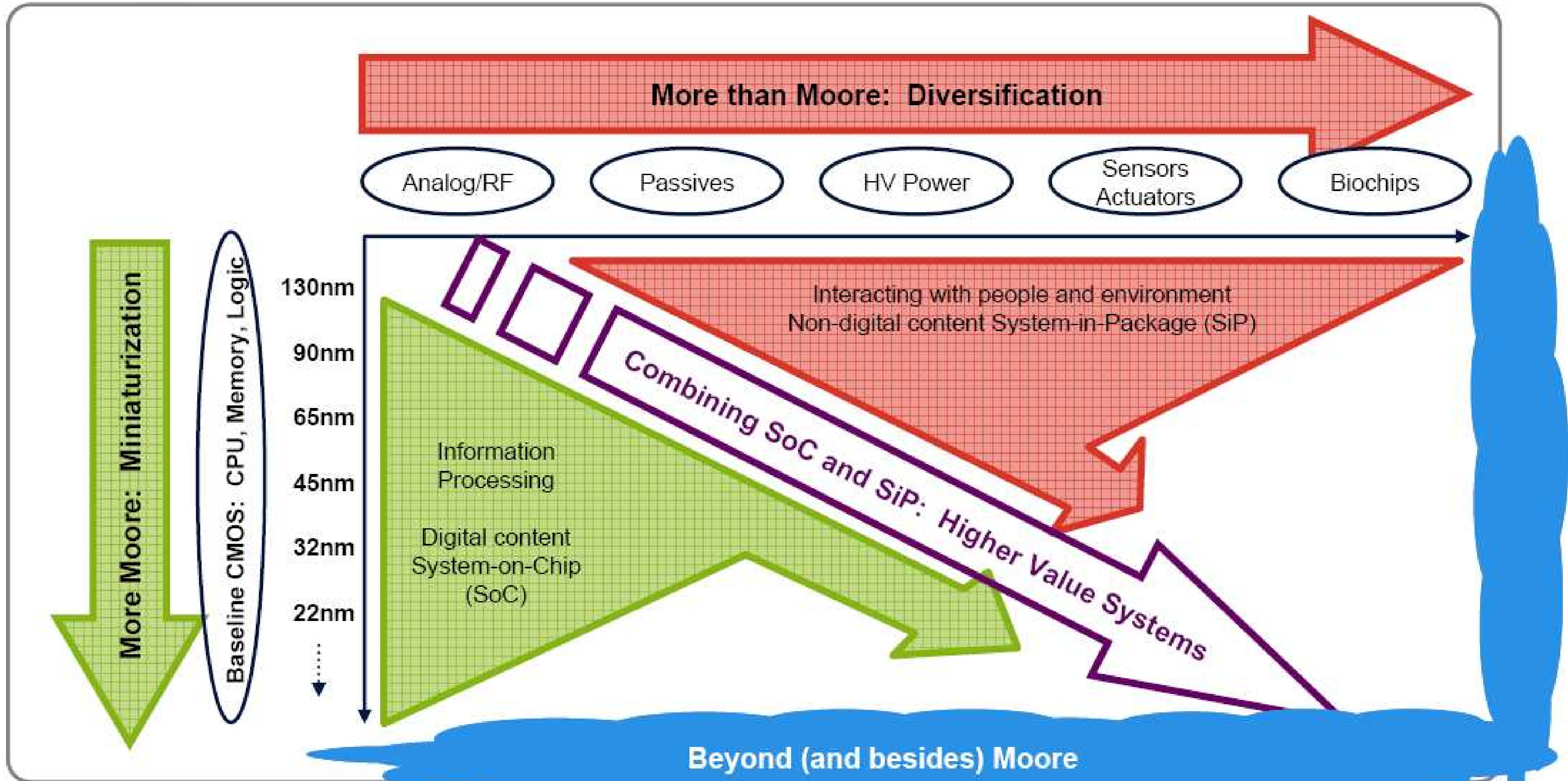
« More, More than, Beyond Moore »

Tomorrow's top added value markets



High growth with 'More than Moore' technologies:
they require **expertise** in all technical domains and in-depth knowledge of the targeted markets *ITRS 2009*

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NEMS scaling laws: is it worth?

- resolution increases
- sensitivity decreases (SBR,SNR) => arrays, actuation,…
- figures of merit pressure and vacuum quality dependent

$$\delta m = \frac{M_{eff}}{Q} \cdot 10^{-(DR/20)}$$

$$DR \propto \sqrt{\frac{\sum S_{noise}}{P_{act}}} = \frac{1}{SNR}$$

ML Roukes et. al. APL (2005)

Parameter	Scaling rule
mass	k^3
stiffness	k
resonant frequency	k^{-1}
mass responsivity	k^{-4}
energy consumption	k^3 [rough estimate]

$$M_{eff} \propto l \cdot w \cdot t$$

$$\kappa_{eff} \propto w \cdot \frac{t^3}{l^3}$$

$$f_0 \propto \sqrt{\frac{\kappa_{eff}}{M_{eff}}} \propto \frac{t}{l^2}$$

$$\Re = \frac{\partial f_0}{\partial M_{eff}} = -\frac{f_0}{2M_{eff}}$$

$$E_P \approx \frac{1}{2} \kappa_{eff} \cdot x_{Max}^2$$

and $x_{Max} \propto t$

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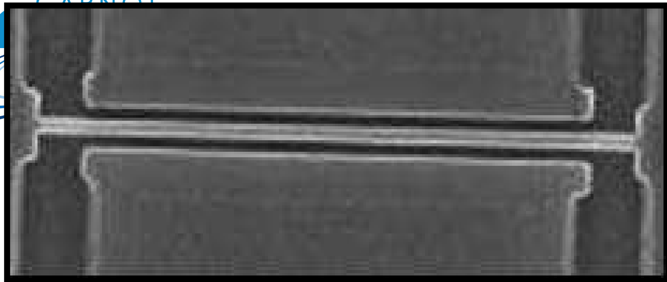
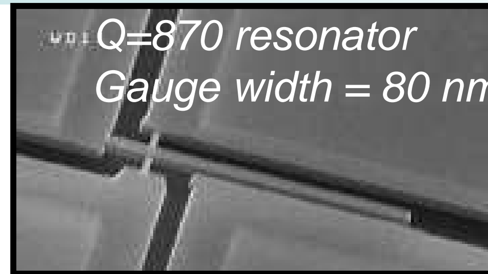
Nanowire used for mass detection

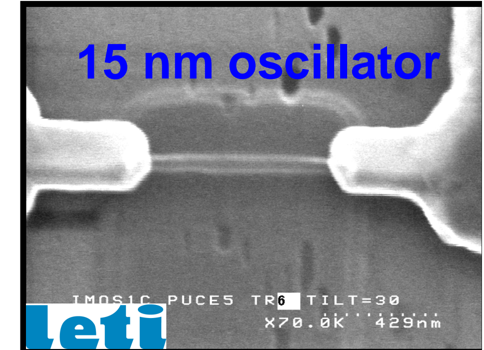


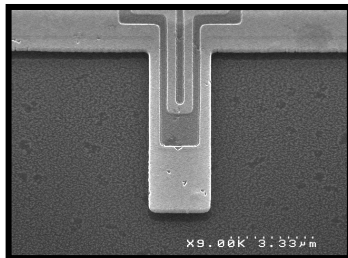
Capacitive actuation & detection



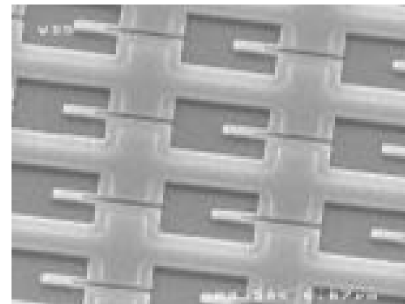
Capacitive actuation & piezo-resistive detection with nanowires

$$\delta m \approx 0.5\ zg / \sqrt{Hz}$$

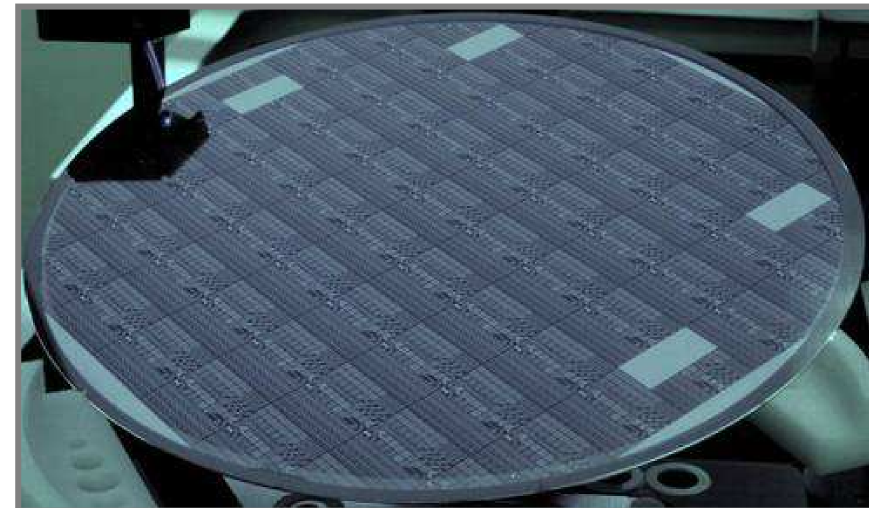




Thermo-elastic actuation & piezo-resistive detection.



NEMS array



- *First 200 mm wafers with 3.5 millions NEMS*
- *Association Nanowire/Resonator ; Cantilever arrays CMOS compatible*

LETI: T.Ernst et al., IEDM 2008, Invited talk
L. Duraffourg et. al, APL 92, 174106 (2008)
E Mille et al, Nanotechnology, 165504, (2010)

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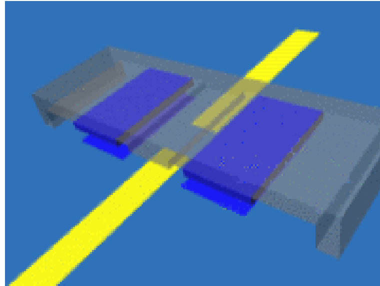
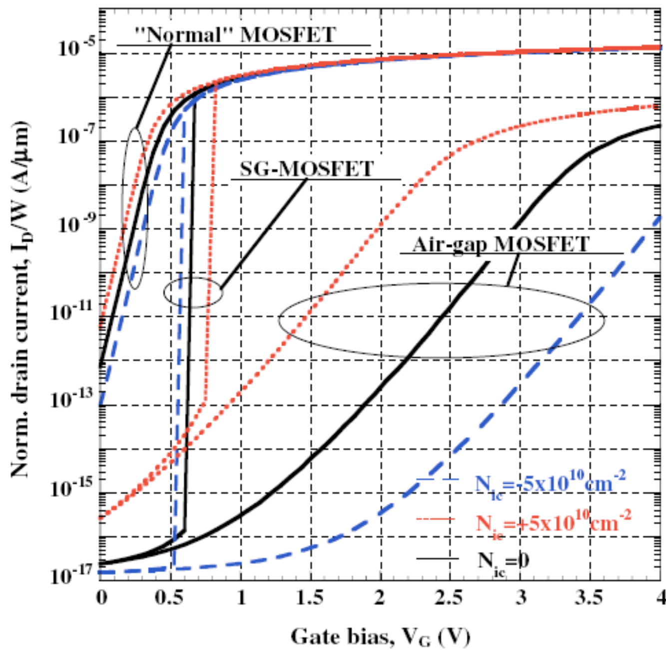
NEMS switch

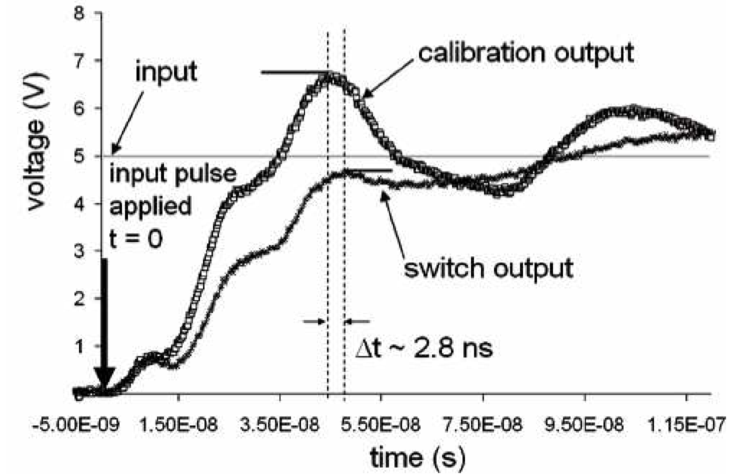




from D. Tsamados et al. Solid-State Elec. 52 1374 (2008)

"high" speed

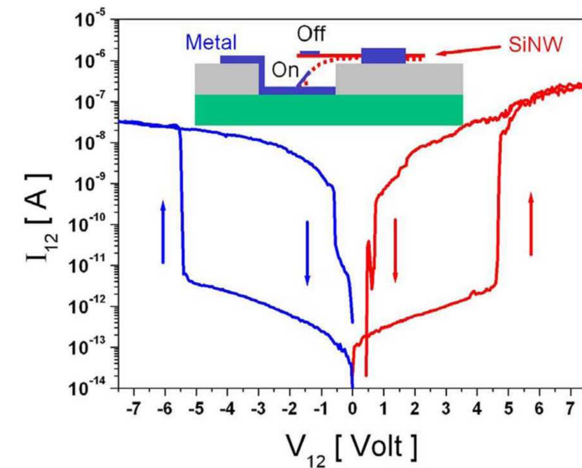
rf



from AB. Kaul et al., Nano Letters 6(5) 942-947 (2006)

bistable

memory



from Q.Li et al.,IEEE Nano 6(2) 256-262 (2007)

high on/off → low power logic

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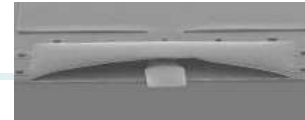
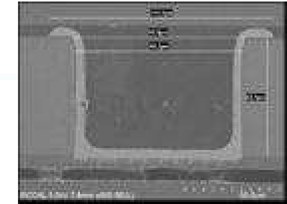
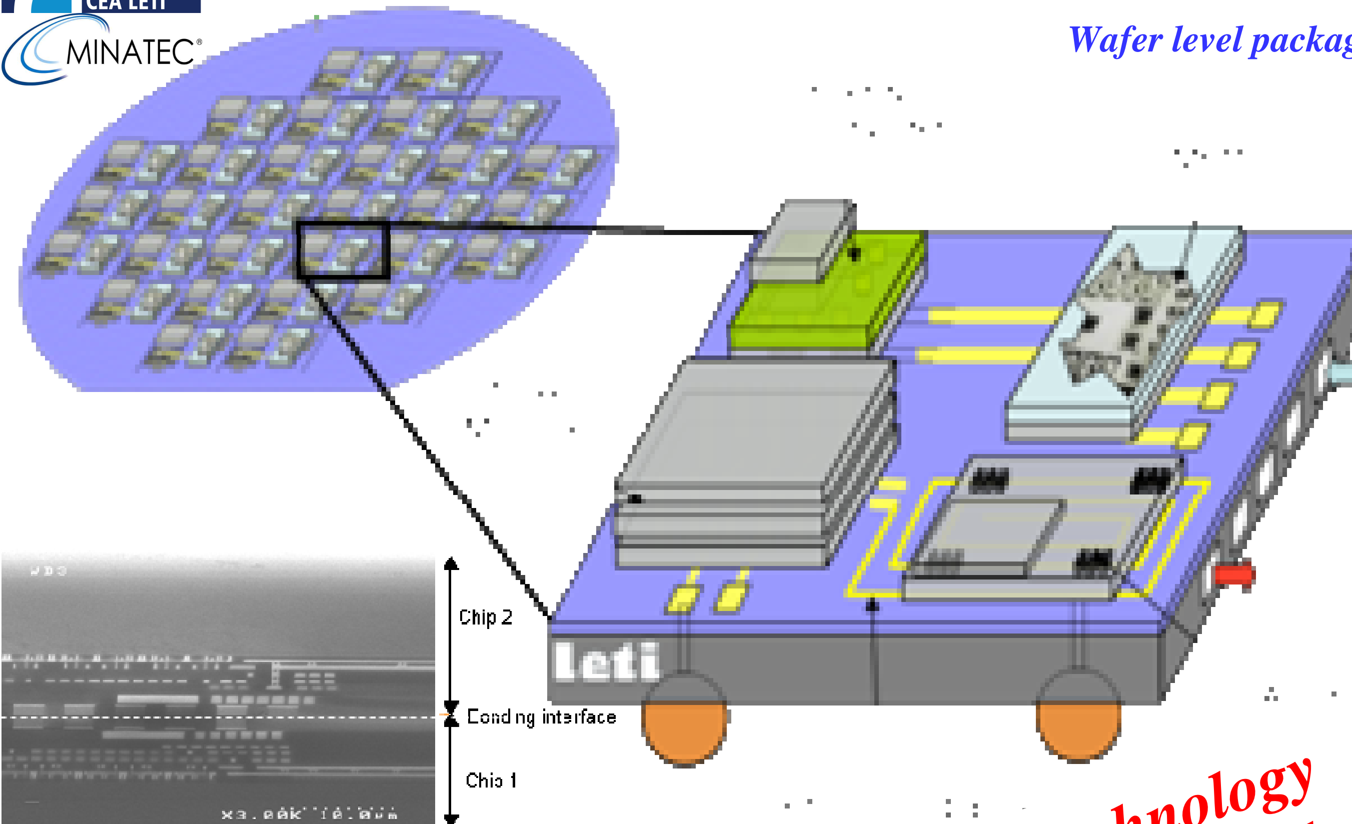
System On Wafer.

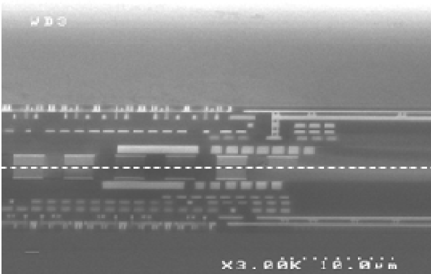


Wafer level packaged MEMS

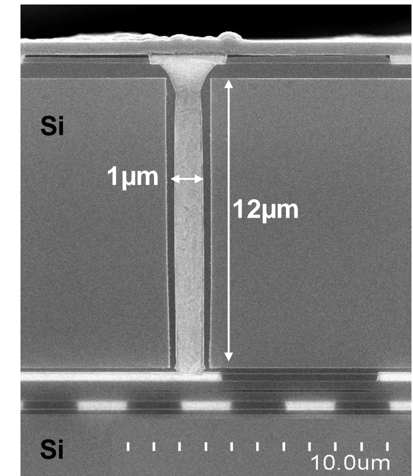


80 µm diameter TSV imagers packaging

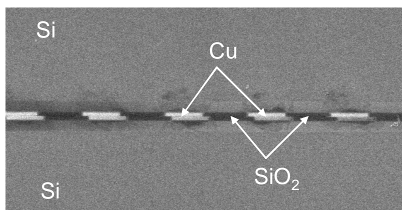




Oxide/Oxide bonding



1 µm diameter
High AR TSV stacked ICs



Copper/Copper bonding

Via belt technology
MEMS + IC stack
Ultra flat 3D
Chip stacking(TSV)
Active Silicon interposer

H… On Silicon
…count
…level

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3D Integration: from imagers to advanced 3D ICs

INSTITUT CARNOT CEA LETI
MINATEC

ST – LETI collaboration

2001

2008

with TSV

VGA cameras (300kpixels)

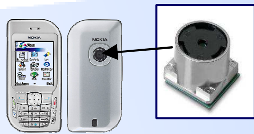
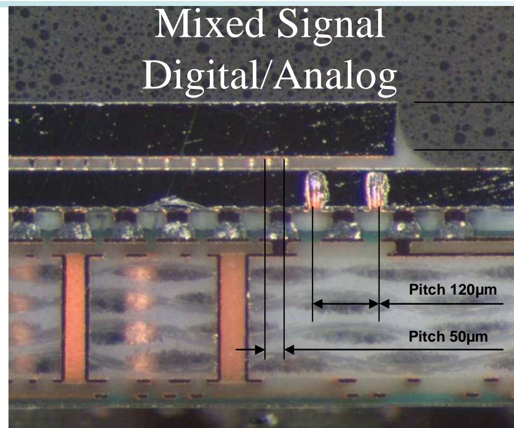
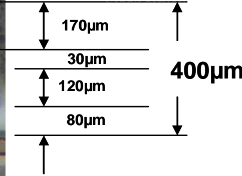
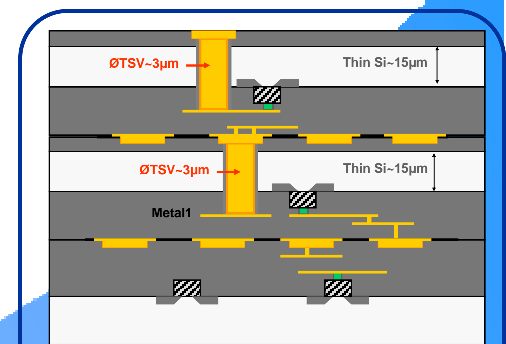


Image-on-Board





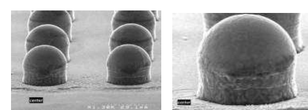
ST – LETI collaboration



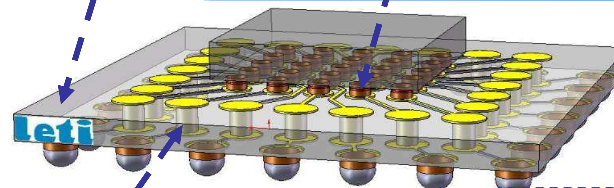
3D-IC

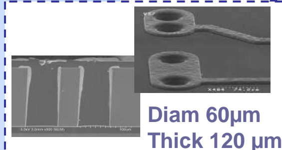
Memory, Processors, Imagers with high density TSV, NEMS…

Thinned wafer (~100 µm)



Die to Die Copper pillars





Diam 60µm
Thick 120 µm

Via Last TSV (Aspect Ratio 2-3)

Die to substrate copper pillars

Active Silicon interposer

3D high density

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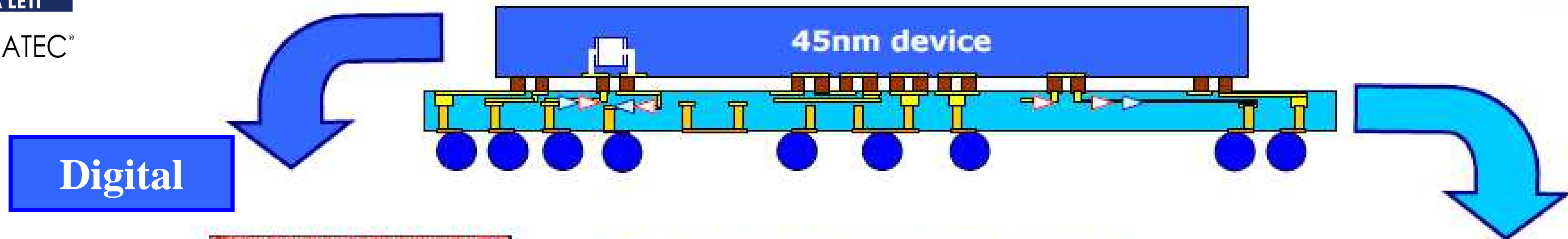
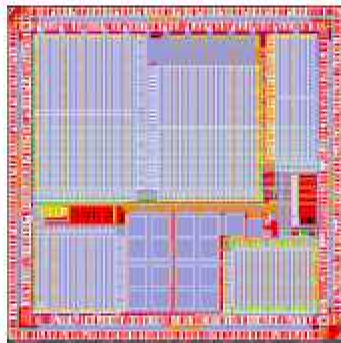
Digital on Analog: the first 3D demo

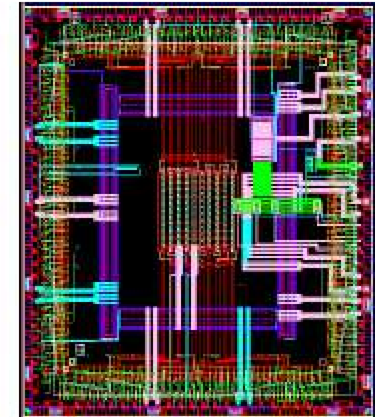


Digital



CMOS 45nm, 25 mm²

- TSV for top and bottom chips access
- Daisy chains & delay chains with F2F, TSV and RDL paths
- Voltage regulator driving a 45nm IP
- Mechanical stress sensors
- Thermal sensors
- IO boundary-scan

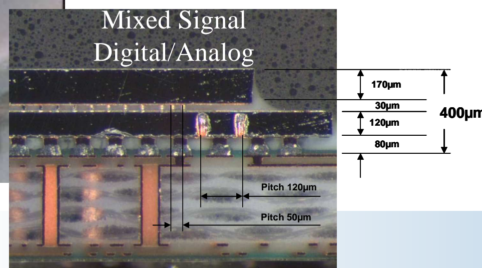


Active interposer, CMOS 0.13µm 32mm²

Analog

- Techno partitioning
- Best IP in best techno node
- Performance & Time to market
- Better scalability

•1056 inter-chip connections
•588 TSV's
•482 bumps
•In BGA 864 lead free balls, 1.0 mm pitch



By courtesy: D43D Workshop - 3D Integration program – P. Ancey Lausanne – 2010, May 27th-28th

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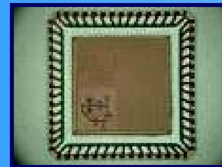
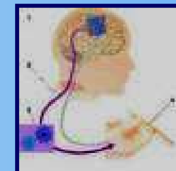
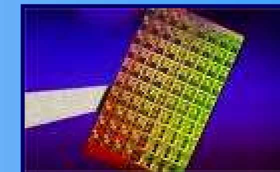
Application Drivers

Great focus on packaging & integration

	MOBILE WIRELESS	CONSUMER	HEALTH	COMPUTING & STORAGE	AUTOMOTIVE
Form Factor	Ultra small TV Tuner , Sharp		Computer control using thoughts	Quad Core Intel	
Cost	 Full tranceiver on Chip, Antenna+RF+ Baseband, Leti			128 GB SSD, Toshiba	
Performance	Nokia N82, 5Mpixel Video capture, coding, transmission	One Chip SetTopBox (STM)		 Intel's Teraflop Chip	

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3D Roadmap: Overview of architectures

ITRS 65nm 45nm 32nm

2007 2009 2012 >2014

Low density 3D via Chip-level bonding

High density 3D via wafer-level bonding

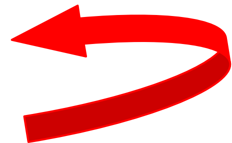
Vertical device on CMOS (NTC, NW, NEMS)

Optical Interconnects

InP/SOI µ-laser 1.6µm 0.5mA

Ge photodetector

Cross talks:
-delay, matching,
-power dissipation
(global temp. increase,
hot spots, reliability, …)



100% filled via

CMOS Image sensor (Sensor + DSP + RAM)

Image Sensor

Digital Signal Processor

Via size=50µm

Via size=5-30µm

3D Stacked memory (NAND, DRAM, …)

Cache memory

CPU

Via size=<5µm

Logic (multicore processor with cache memory)

Sensor I/O RF Power Analog DRAM / NVM Cache Memory CPU

Via size=<2µm

Multi-level 3D IC (CPU + cache + DRAM + Analog + RF + sensor + IO)

Targets for MEDEA+ project

Vertical Interconnect Density (cm^{-2}): 1E9, 1E8, 1E7, 1E6, 1E5, 1E4, 1E3, 1E2, 10, 1

Vertical 3D via pitch (µm): 1000, 100, 10, 1, 0.1

Flip chip solder bump min pitch

ITRS C65nm min Global metal pitch

ITRS C65nm M1 min pitch

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Conclusion :Nanoelectronics CMOS from Devices to Systems Perspectives

- **Si CMOS: Nanoelectronics Base platform beyond ITRS**
- **Durable Low Power solutions:**

  health, environment, quality of life, energy, IST,…
- **Low Power consumption: major challenge (sub 1V VDD CMOS).**

  => Device/ system architecture optimization:

  Thin Films Gate All Around nanowires, low slopes,layout, 3D

  => Opportunities for new materials on Silicon

  (Ge, revised low BG III-V, Carbon,…) to co-integrate from LSTP to HP.
- **Heterogeneous 3D co-Integration on Si, Low Power:**

  Monolithic/Sequential 3rd dimension in device. New active materials

  Reconfigurability with NVM ; NV Logic

  System On Wafer: 2 to 3D heterogeneity functions & chips

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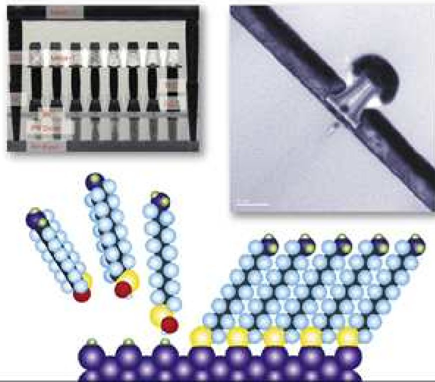
Innovation for industry

Electronic Device Architectures for the Nano-CMOS Era

From Ultimate CMOS Scaling to Beyond CMOS Devices



Simon Deleonibus
Editor

Available at Amazon.com or any good bookstores.

Electronic Device Architectures for the Nano-CMOS Era

From Ultimate CMOS Scaling to Beyond CMOS Devices

edited by **Simon Deleonibus** (*CEA-LETI, France*)

Cloth July 2008 978-981-4241-28-1

★ Discusses the scaling limits of CMOS, the leverage brought by new materials, processes and device architectures (HiK and metal gate, SOI, GeOI, Multigate transistors, and others), the fundamental physical limits of switching based on electronic devices and new applications based on few electrons operation

★ Weighs the limits of copper interconnects against the challenges of implementation of optical interconnects

★ Reviews different memory architecture opportunities through the strong low-power requirement of mobile nomadic systems, due to the increasing role of these devices in future circuits

★ Discusses new paths added to CMOS architectures based on single-electron transistors, molecular devices, carbon nanotubes, and spin electronic FETs

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